
Introduction to Electronics for Particle Physics Experiments

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Microelectronics section



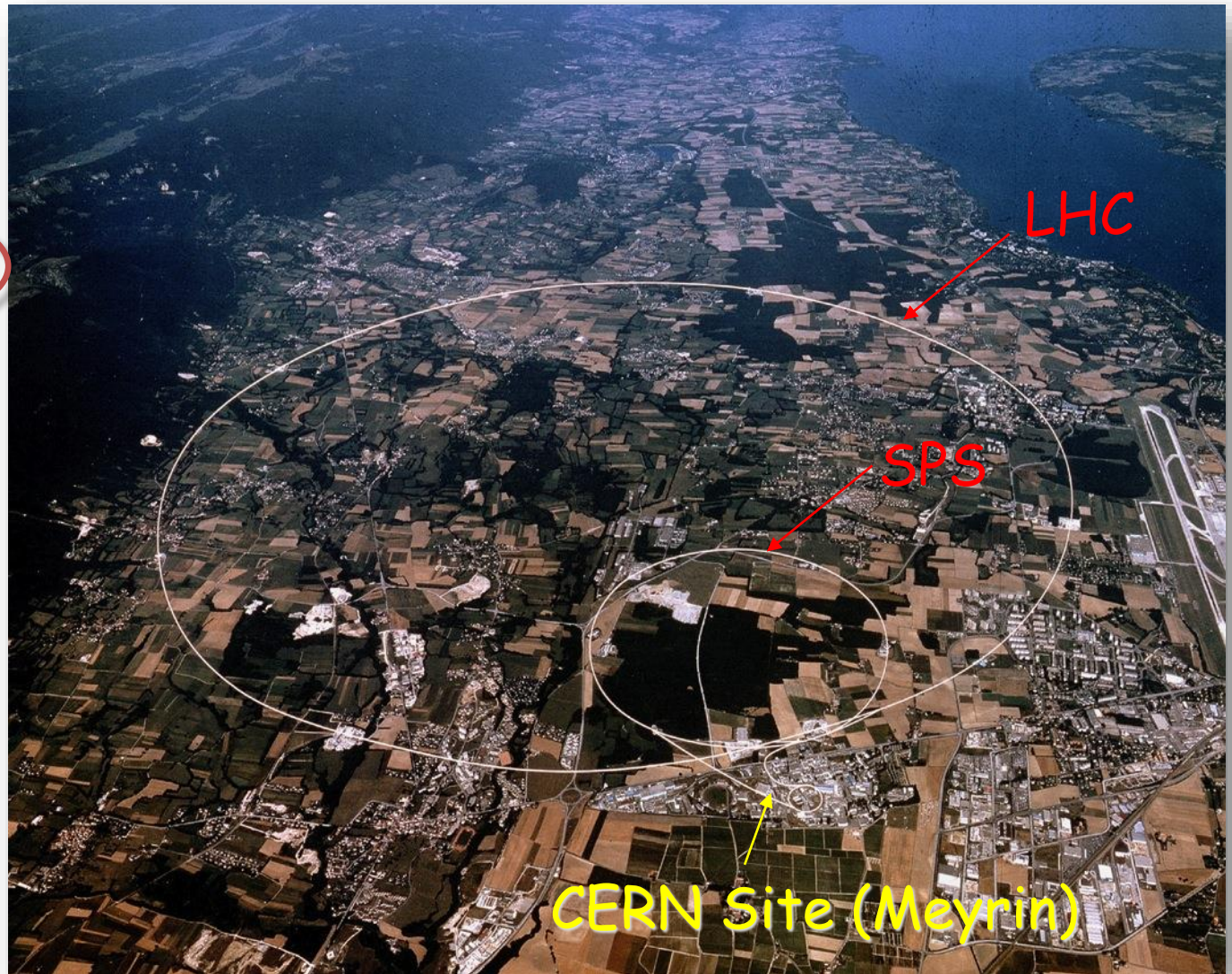
Η αποστολή του CERN

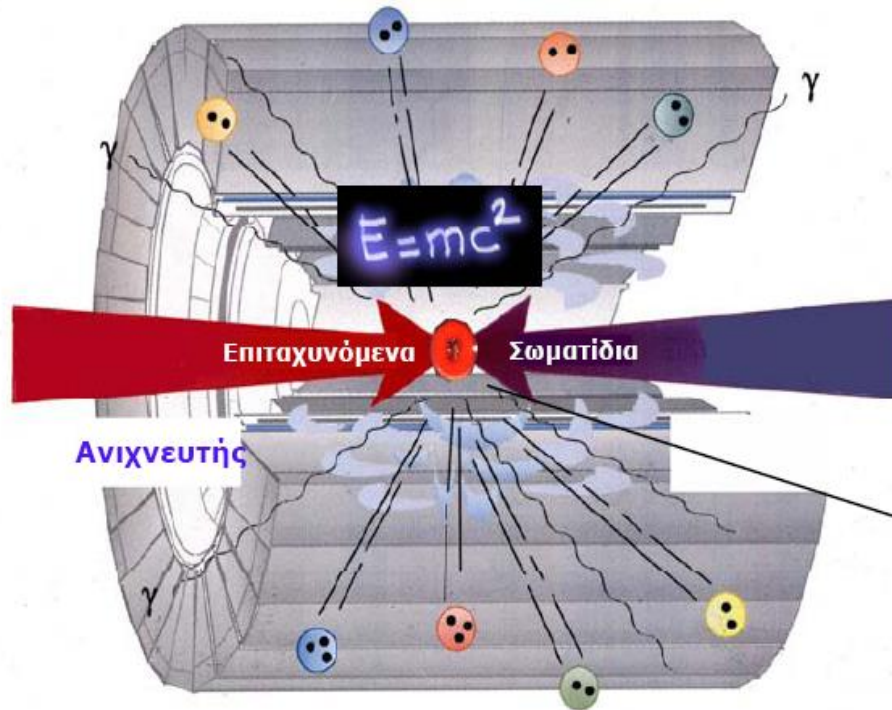
Έρευνα &
Ανακάλυψη

Τεχνολογία

Συνεργασία

Εκπαίδευση &
Κατάρτιση





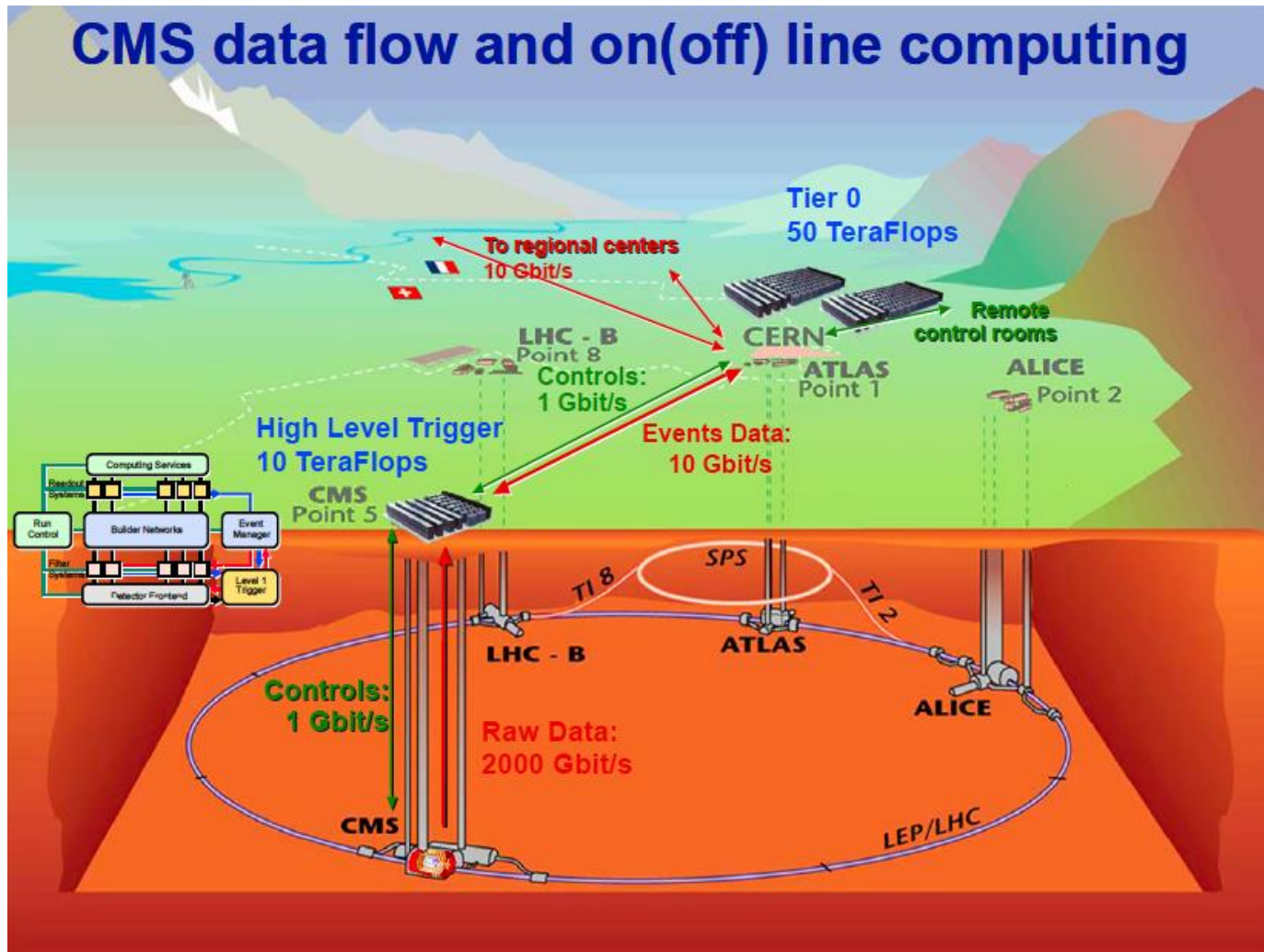
1) Συγκέντρωση ενέργειας στα σωματίδια (**επιταχυντής**)

2) **Σύγκρουση** σωματιδίων (δημιουργία συνθηκών ανάλογων του Big Bang)

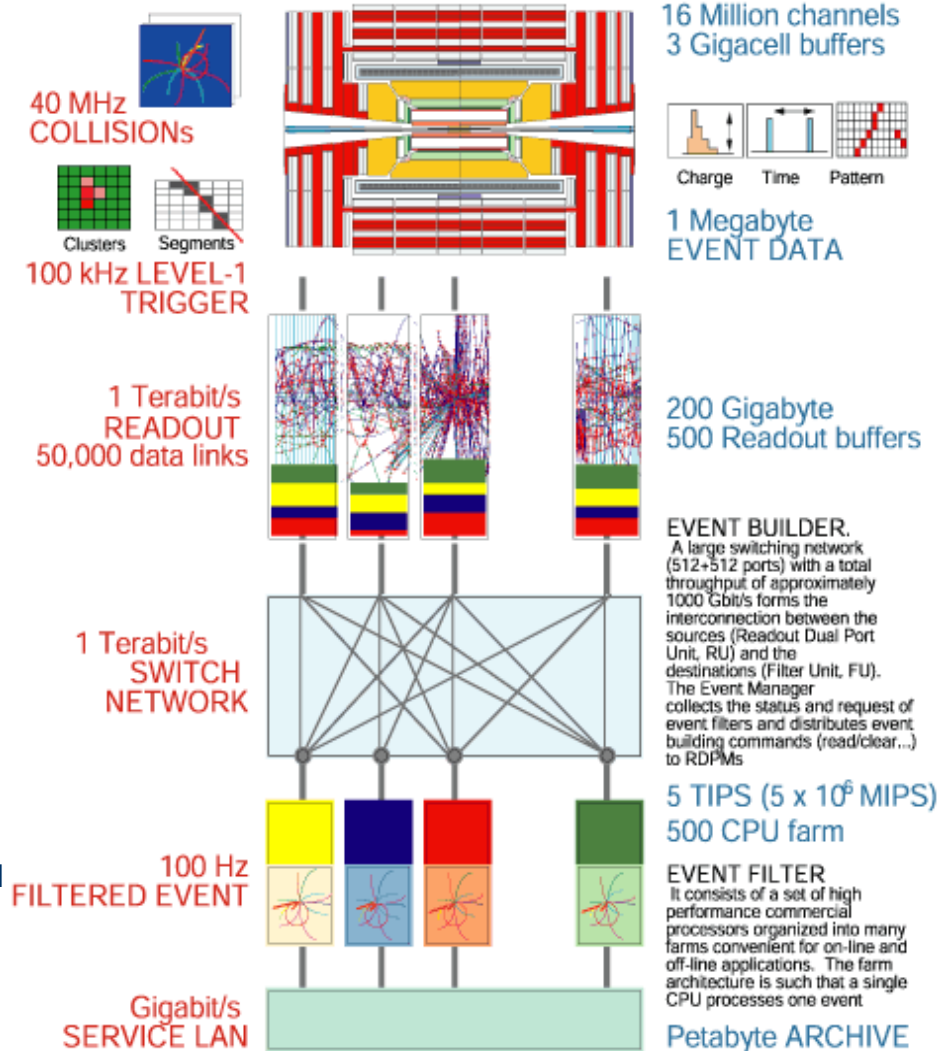
3) Αναγνώριση παραγόμενων σωματιδίων από τον **Ανιχνευτή** (έρευνα για νέα φαινόμενα)

- Τα Σωματίδια συγκρούονται με ταχύτητες παραπλήσιες με αυτή του φωτός με αποτέλεσμα την παραγωγή νέων σωματιδίων. Η διαδικασία αυτή δίνει πληροφορίες για τους μηχανισμούς αλληλεπίδρασης των σωματιδίων και και τους θεμελιώδης φυσικούς νόμους που τα διέπουν.

The flow of Physics data at LHC



- $40 \cdot 10^6$ φωτογραφίες το δευτερόλεπτο
- 20 συγκρούσεις ανά φωτογραφία
- Το πρώτο φιλτράρισμα των μετρήσεων γίνεται στους ανιχνευτές δίνοντας $100 \cdot 10^3$ φωτογραφίες ανά δευτερόλεπτο
- Το δεύτερο φιλτράρισμα των μετρήσεων γίνεται από συστοιχίες υπολογιστών δίνοντας 1 φωτογραφία ανά δευτερόλεπτο για εγγραφή και μετέπειτα ανάλυση
- Τα πειράματα του LHC παράγουν 10-15 Petabytes δεδομένων κάθε χρόνο (20 εκατομμύρια CDs!)
- Για την ανάλυση των δεδομένων χρειάζεται η υπολογιστική ισχύς που αντιστοιχεί σε $\sim 100,000$ γρήγορους μοντέρνους επεξεργαστές.





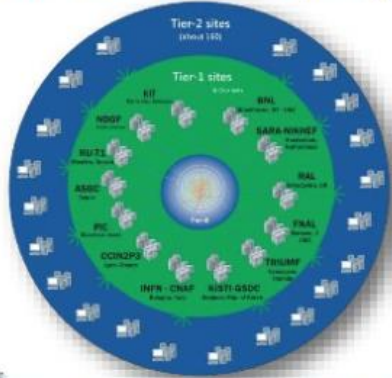
Παγκόσμιο Υπολογιστικό Δίκτυο

The Worldwide LHC Computing Grid

Tier-0
(CERN and Hungary):
data recording,
reconstruction and
distribution

Tier-1: permanent
storage, re-processing,
analysis

Tier-2: Simulation,
end-user analysis



-170 sites,
42 countries

-750k CPU cores

600 PB of storage

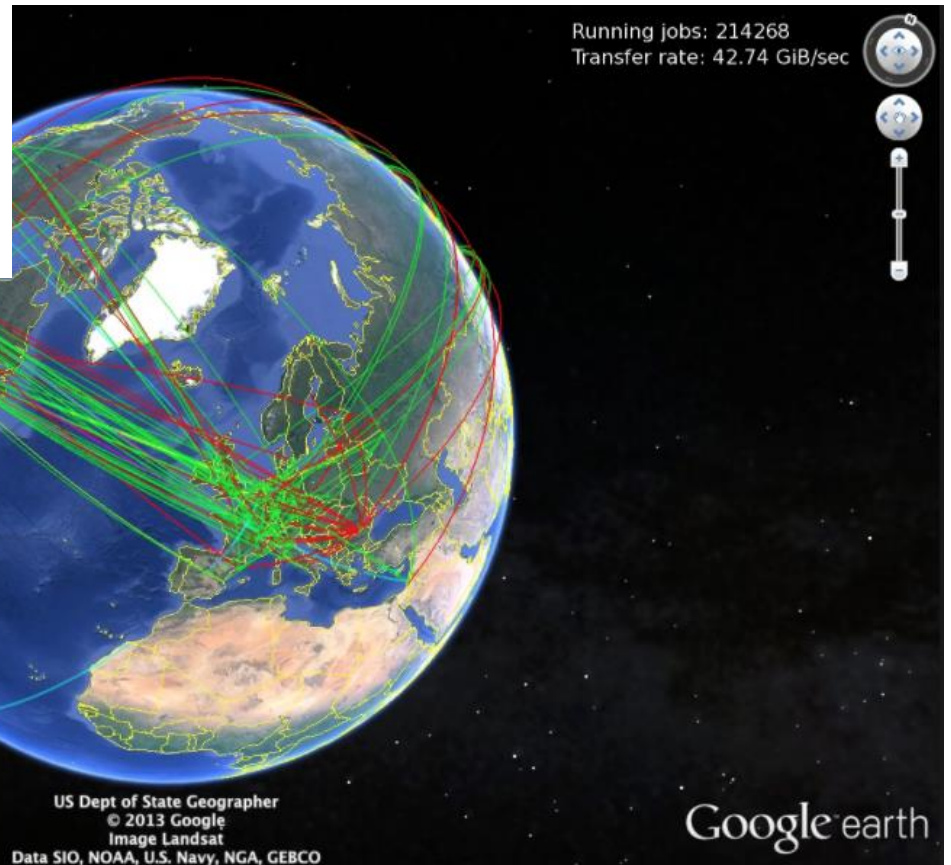
> 2 million jobs/day

10-100 Gb links

WLCG:

An international collaboration to distribute and analyse LHC data

Integrates computer centres worldwide that provide computing and storage resource into a single infrastructure accessible by all LHC physicists



Running jobs: 214268
Transfer rate: 42.74 GiB/sec

US Dept of State Geographer
© 2013 Google
Image Landsat
Data SIO, NOAA, U.S. Navy, NGA, GEBCO

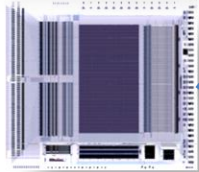
Google earth



Microchips for Megastructures

On-detector ASIC

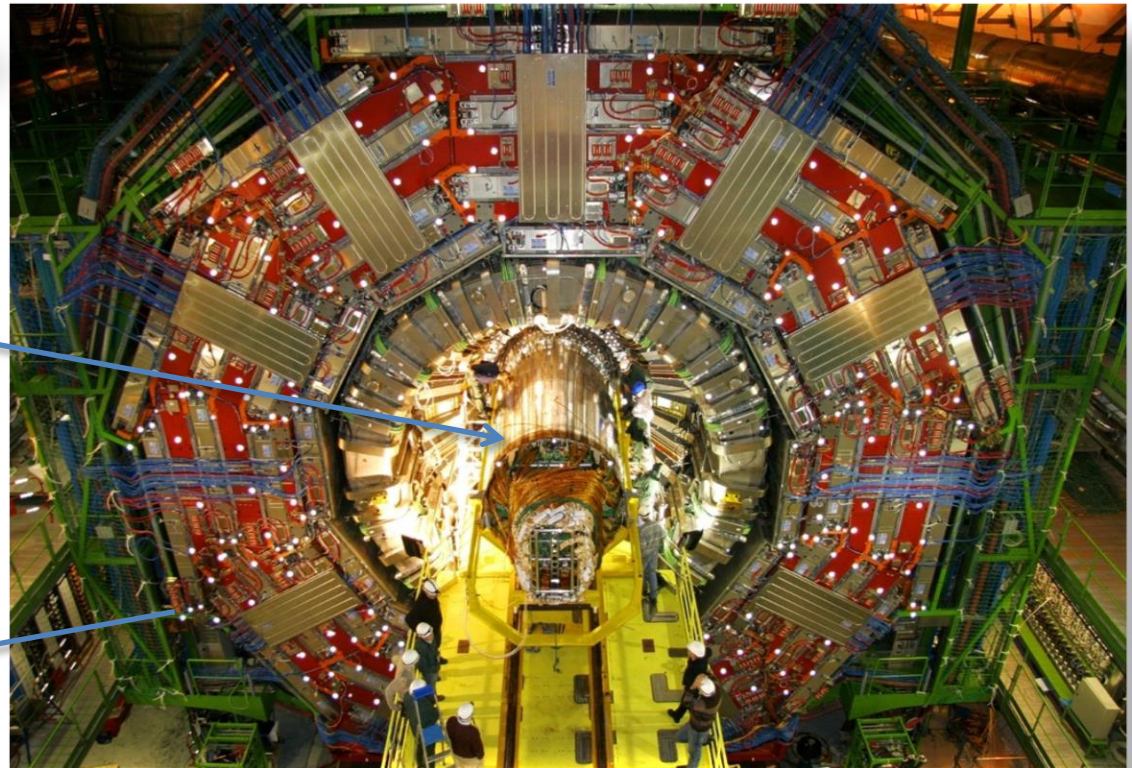
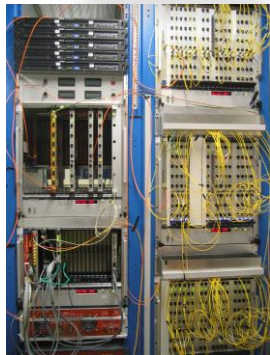
CMS experiment at the LHC accelerator at CERN



Silicon Tracker Hybrid



Off-detector electronics





ASICs στη Φυσική Υψηλών Ενέργειών

- ASIC Application-Specific Integrated Circuits
Ολοκληρωμένα Κυκλώματα εξειδικευμένης εφαρμογής
- Ιδιαίτερα εξειδικευμένες λειτουργίες
 - Ειδικές τεχνικές επεξεργασίας σήματος
 - Υψηλή ανάλυση και μεγάλο δυναμικό εύρος
- Πολύ μεγάλος αριθμός καναλιών ανάγνωσης
 - Χαμηλή κατανάλωση ενέργειας
- Περιβάλλον έντονης ακτινοβολίας
 - TID (Total Ionizing Dose) of 500 Mrads up to 1 Grad
 - Space applications requirements: up to 200 Krads
 - SEE (Single Event Effects)
 - Particle fluence $\sim 10^{15} \text{ cm}^{-2}$ (inner tracker layers)

Silicon Strip Detector electronics

Silicon-strip detector

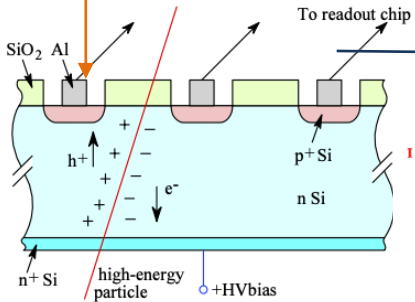
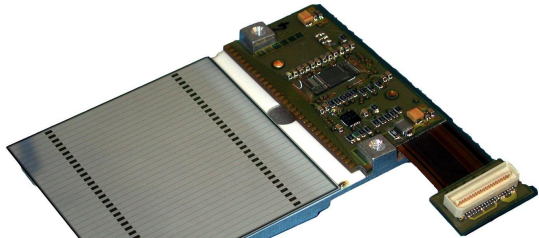
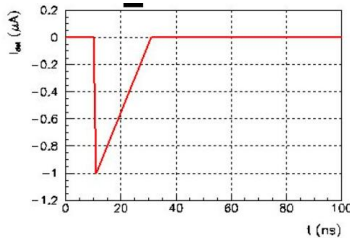
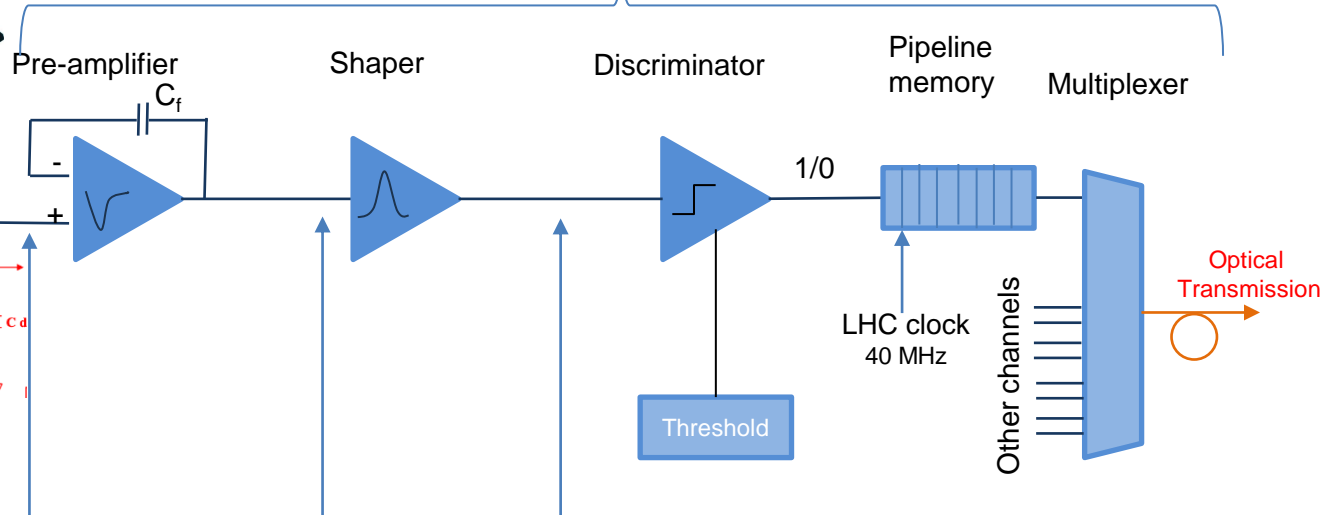
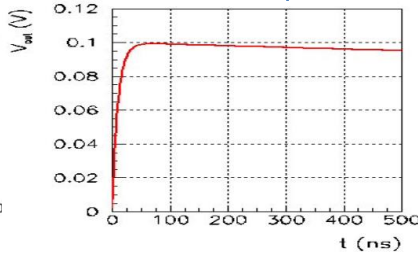


Fig.4: Schematic cross-section of a typical silicon strip detector.

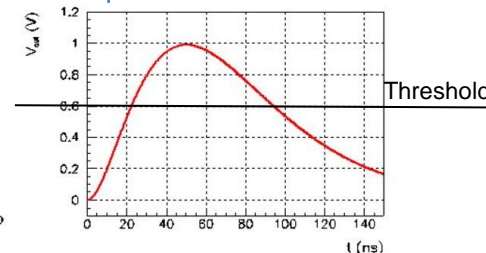
On-detector electronics ASIC (Application Specific Integrated Circuit)



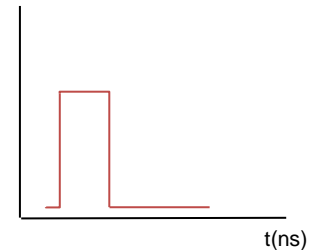
Very small signal (~fC)
Needs amplification



Charge-sensitive amplifier
 $V = -Q/C_f$



Predefined signal shape
Noise reduction by
optimizing useful bandwidth



Digitized signal (1/0)
Signal above a preset
threshold

Silicon Strip Detector electronics

Silicon-strip detector

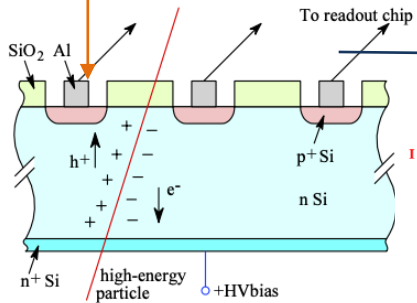
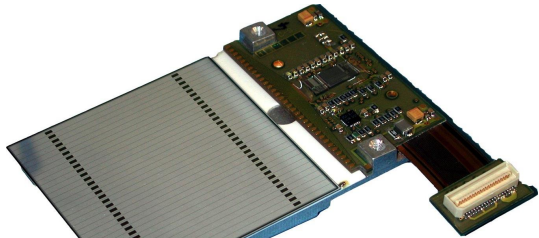
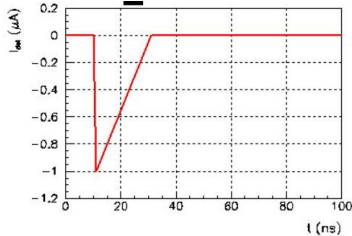
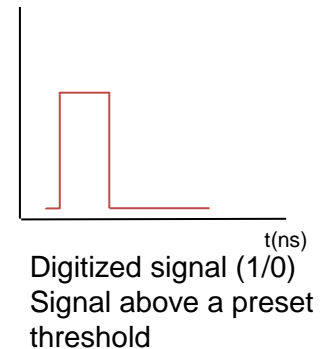
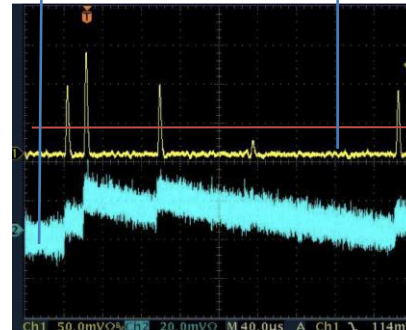
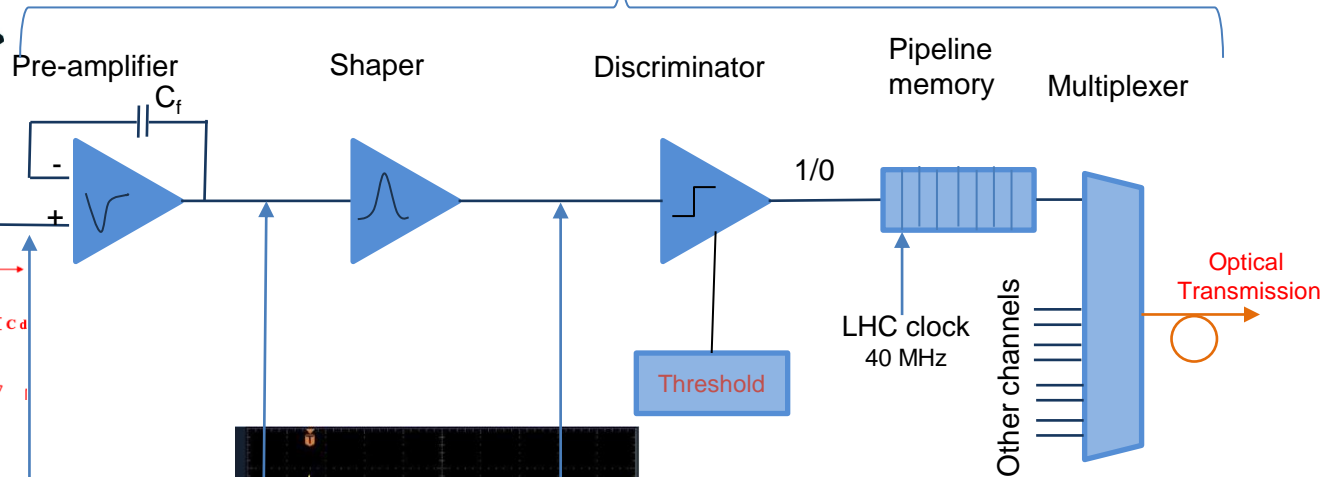


Fig.4: Schematic cross-section of a typical silicon strip detector.



Very small signal ($\sim fC$)
Needs amplification

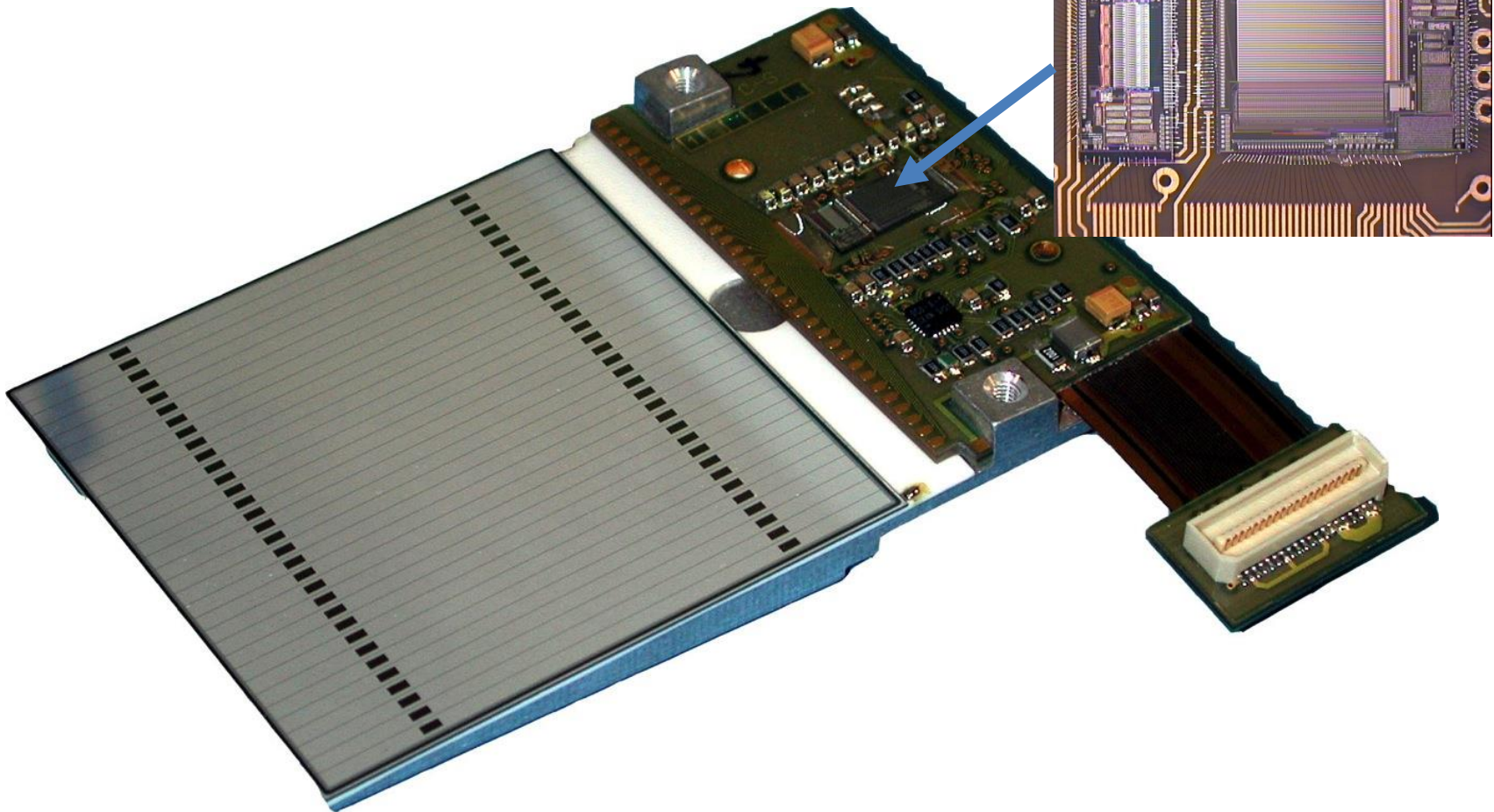
On-detector electronics ASIC (Application Specific Integrated Circuit)



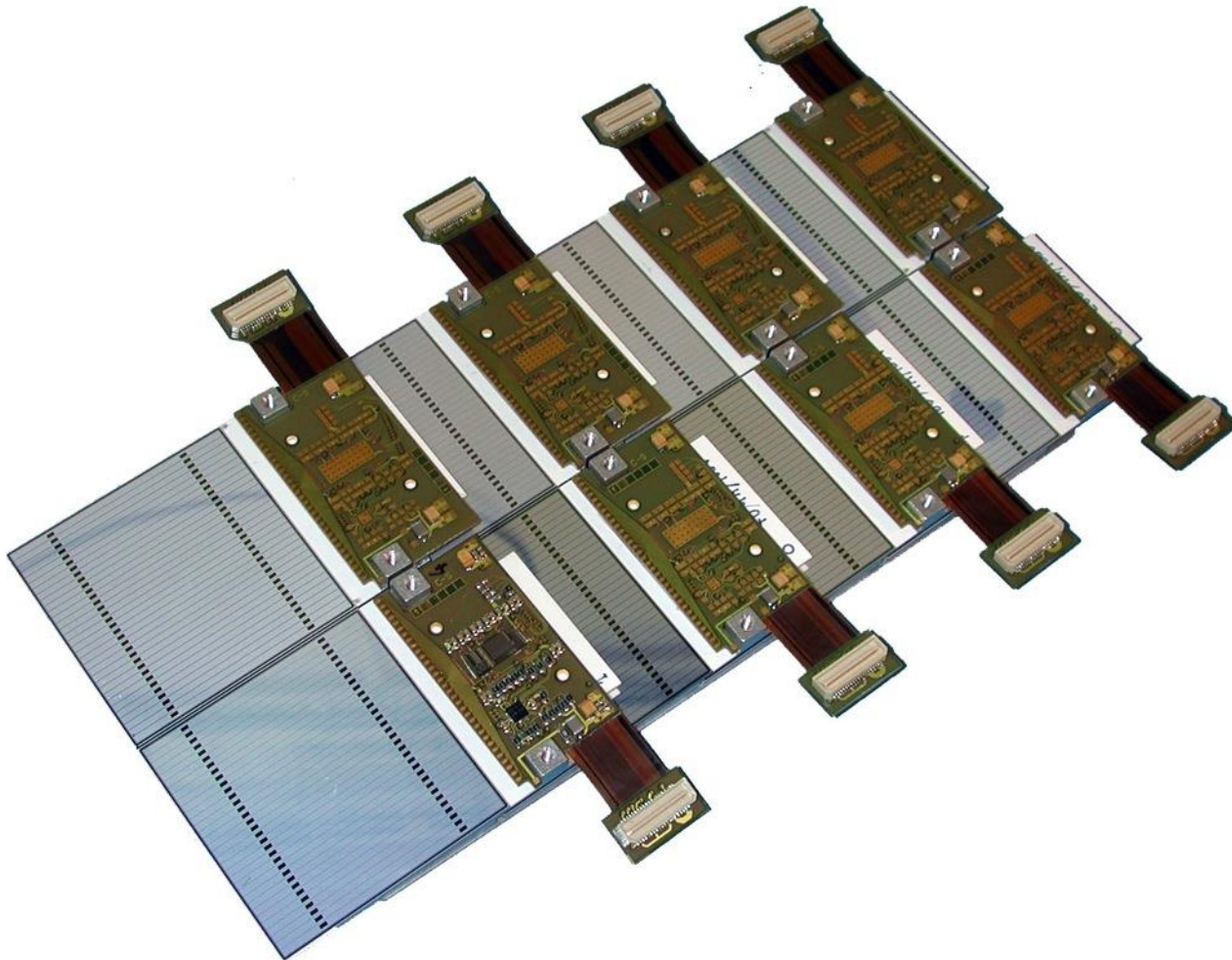
On-detector ASICs

ASIC (Application Specific Integrated Circuits)

CMS Preshower Detector

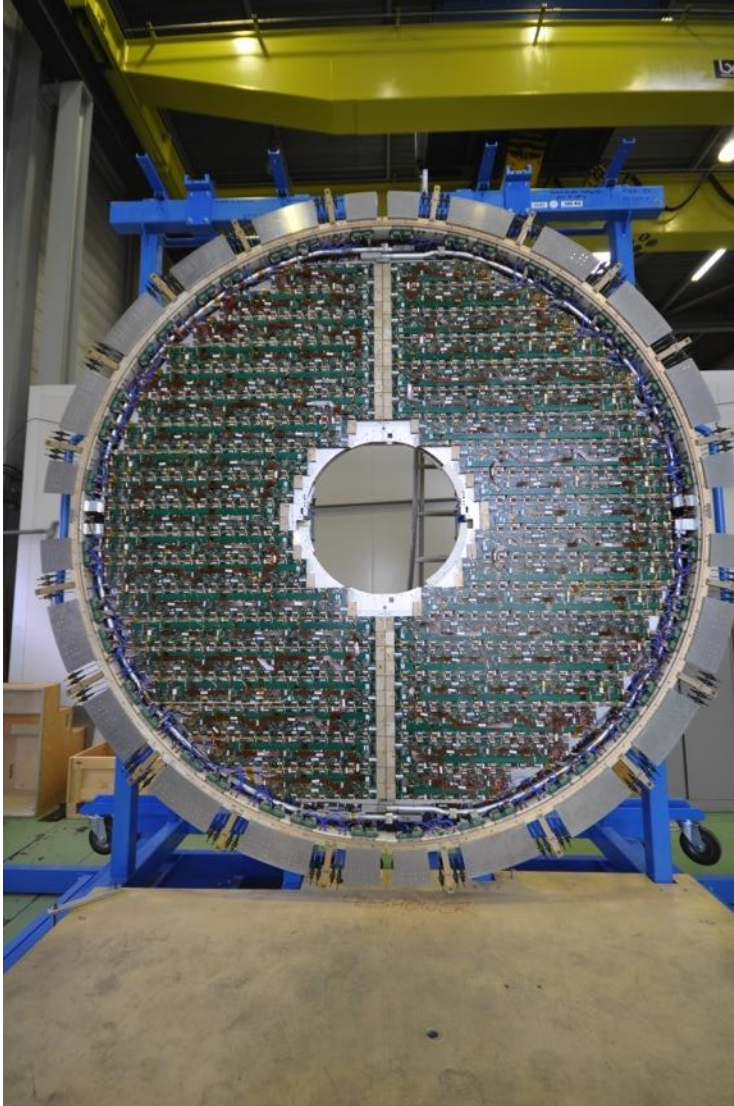


Sensor modules with ASICs

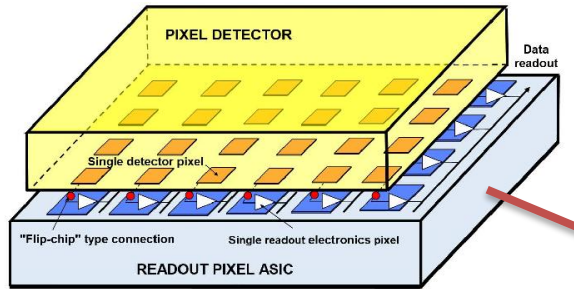




Detector Assembly

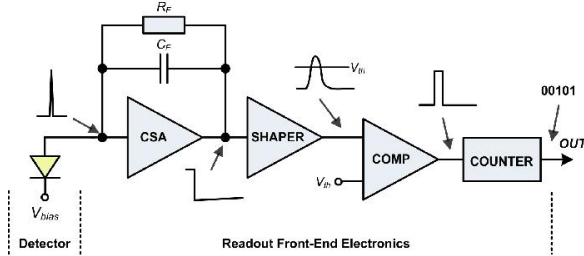


Pixel Detector electronics

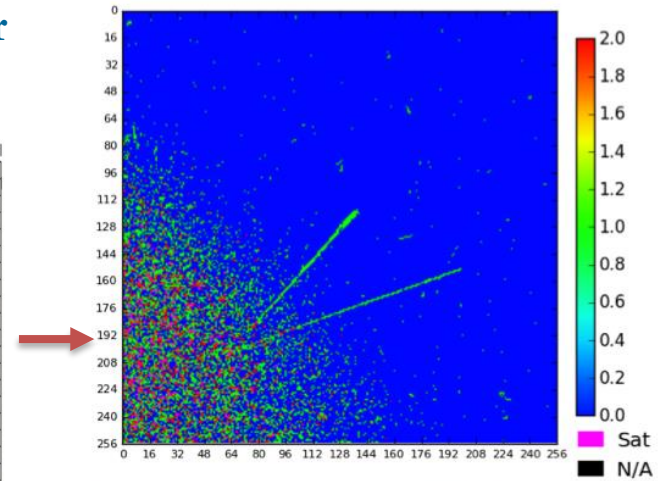
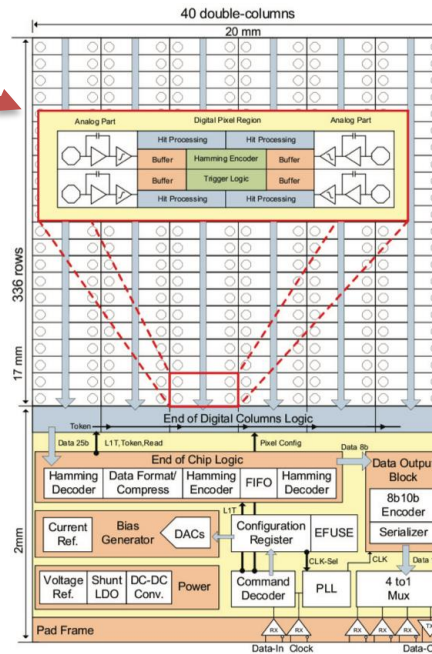


(a)

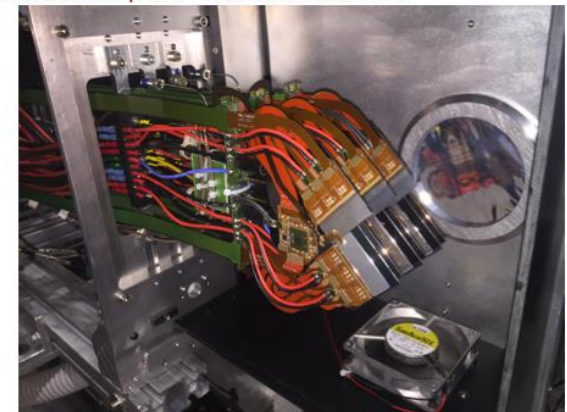
Velopix readout ASIC for the LHCb detector



(b)



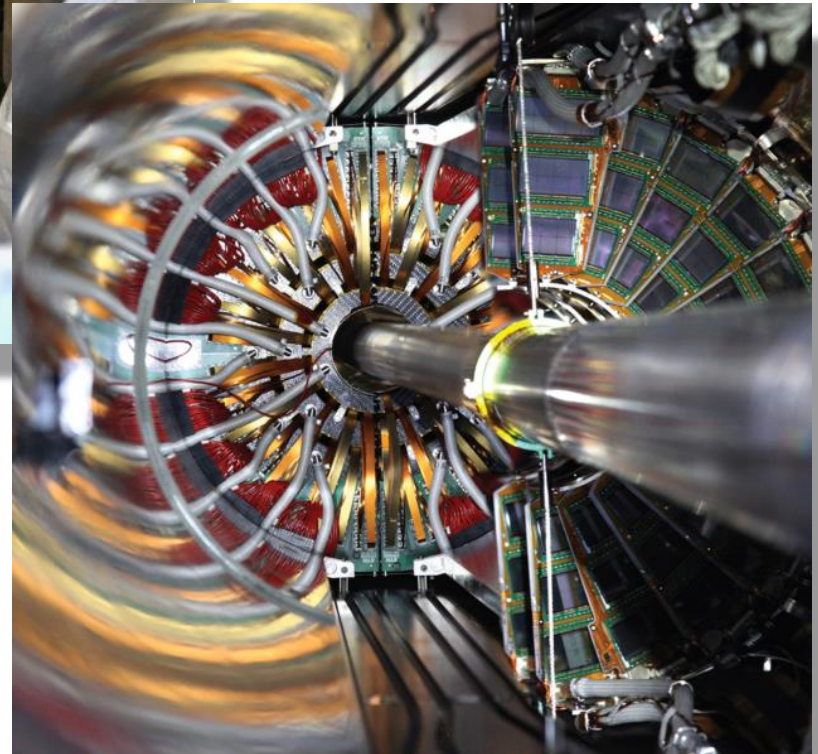
first data with proton beam over GWT link



test setup with beam window



CMS Pixel Inner Tracker

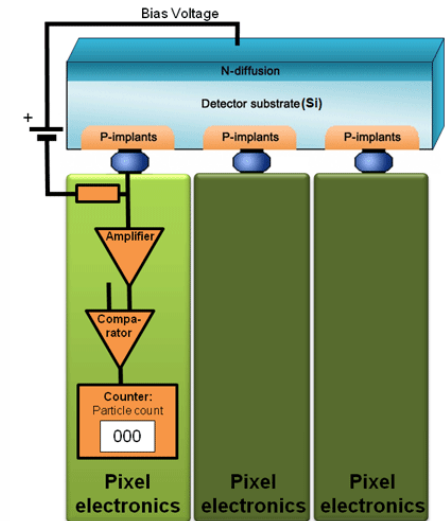
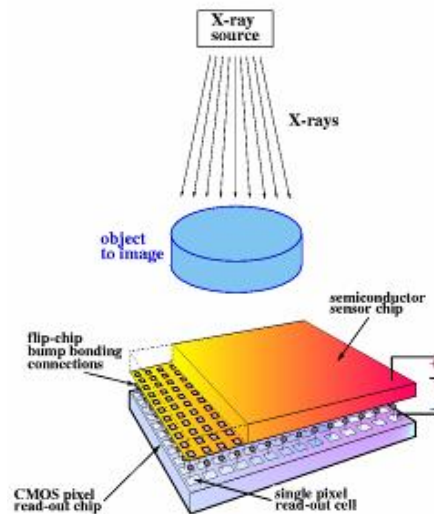
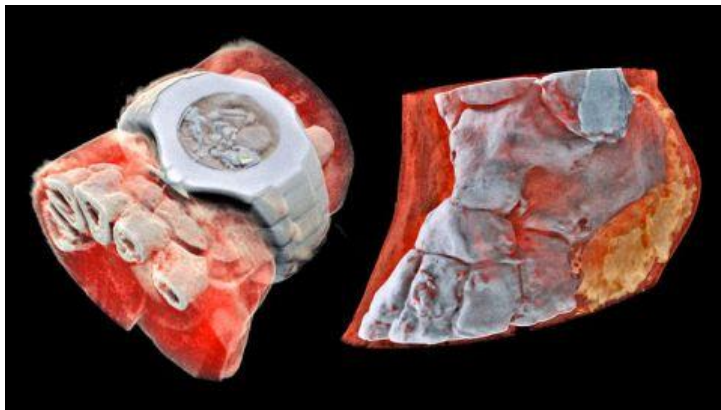
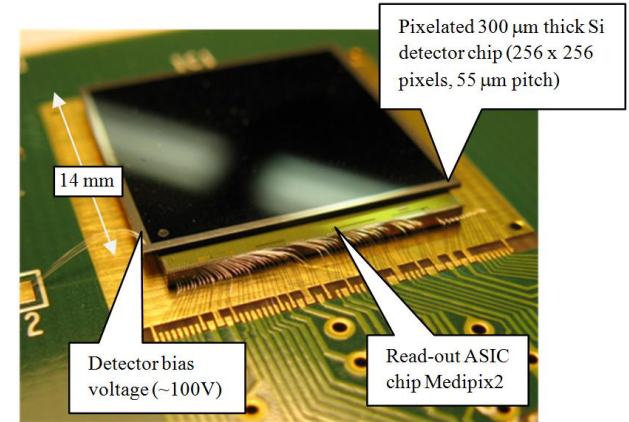


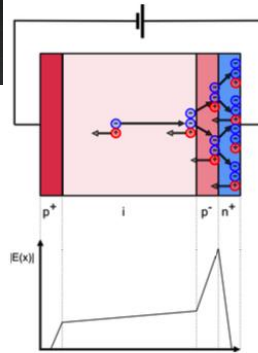
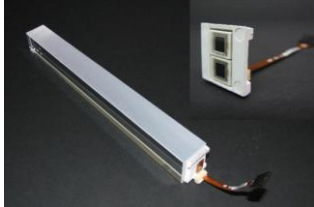
Pixel Sensors in Medical Imaging

New X-ray technology produces striking 3D images in full colour

A new medical imaging device uses technology developed by particle physicists to produce full colour, 3D images of the human body.

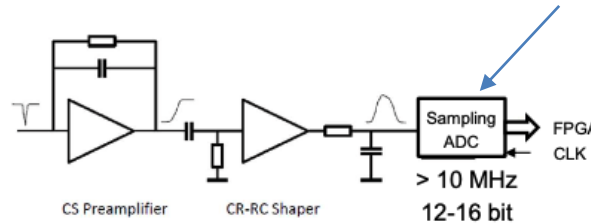
A hybrid detector capable of counting each individual particle hitting the pixels and measure its energy.





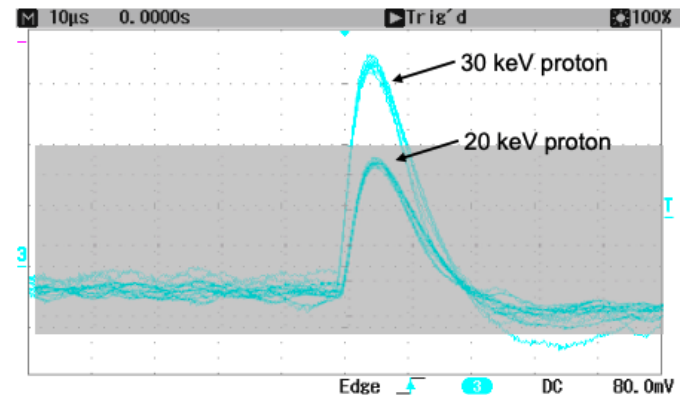
- Lead tungstate crystals
- Avalanche Photo-diodes
Reverse-biased p-n junction
- Primary photoelectrons accelerated in electric field → avalanche
- Generated charge is proportional to deposited energy

Analog to Digital Converter (ADC)

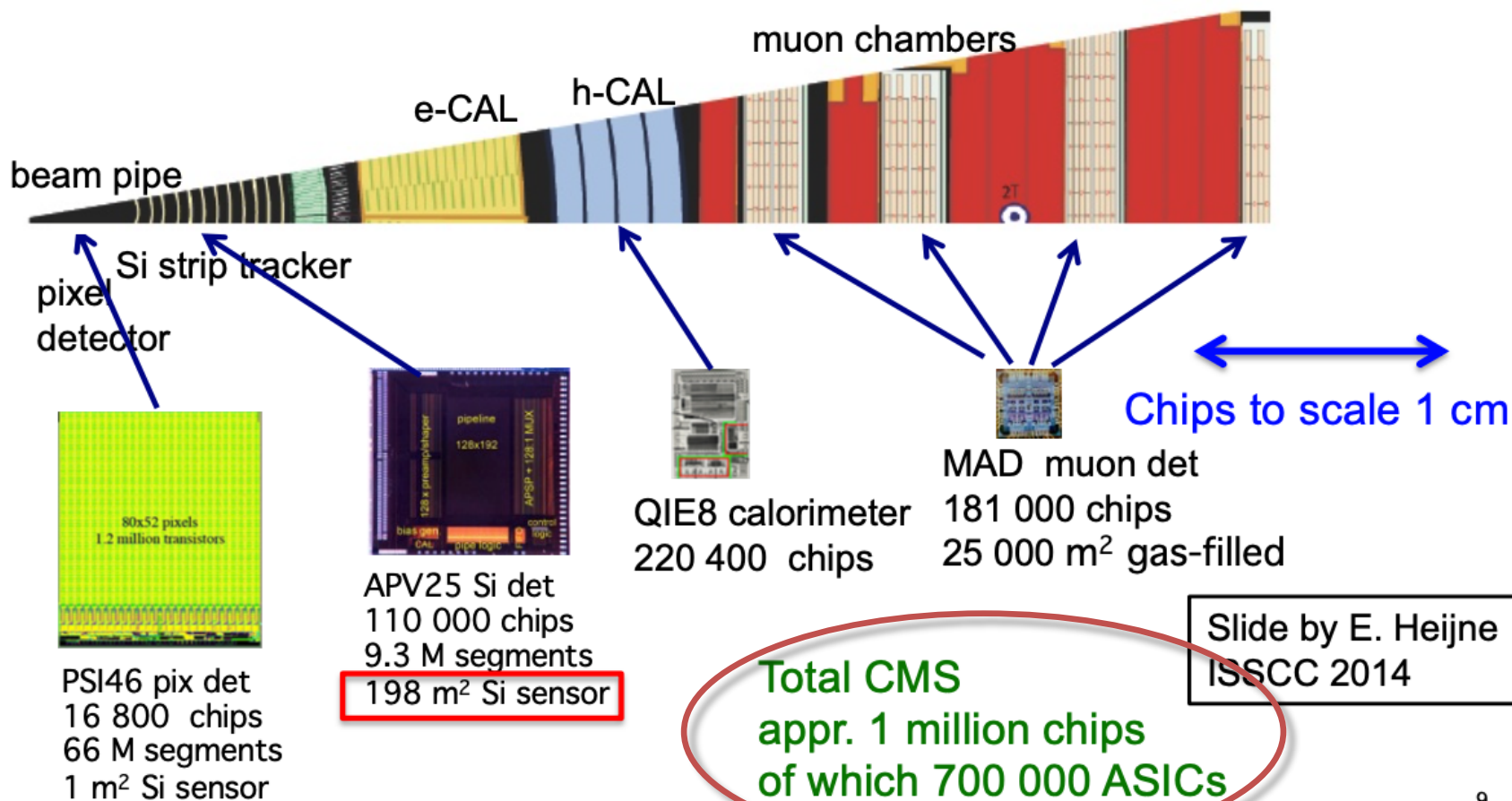


Created charge proportional to energy deposit
 ⇒ Amplitude measurement
 ⇒ Signal Time defines EVENT TIME

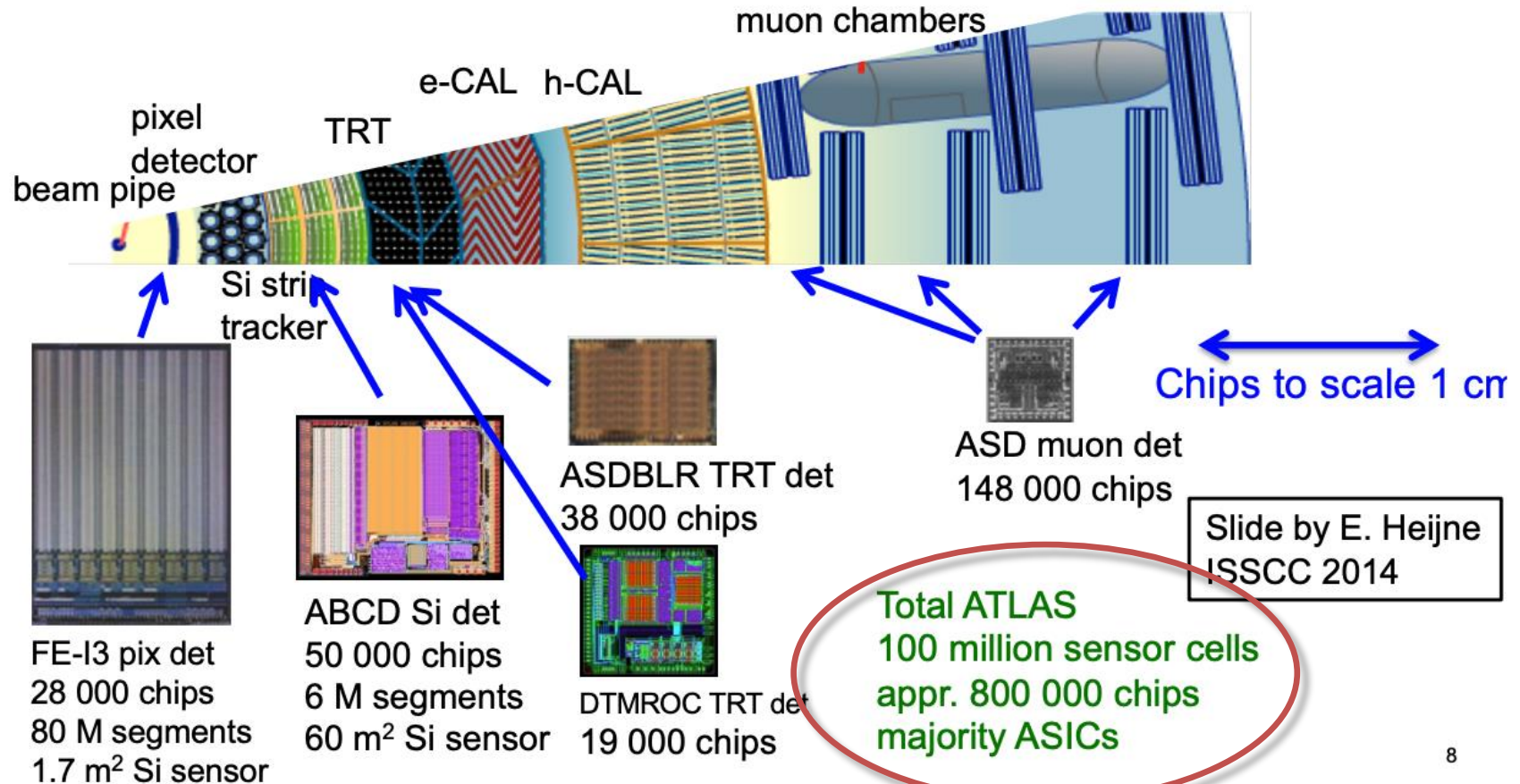
- Charge-sensitive (CS) preamplifier
- Shaping: CR differentiator and RC integrator



Some examples of ASICs in CMS



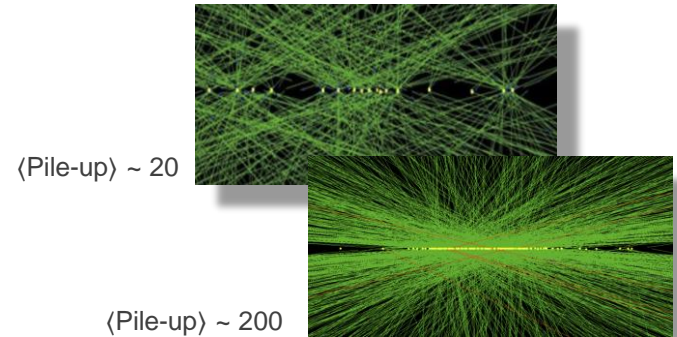
Some examples of ASICs in ATLAS



CMS Phase-2 upgrade challenges

- **LHC → HL-LHC:** sustained luminosity of $5 \times 10^{34} \text{ cm}^{-2}\text{s}^{-1}$

- From 20 → 200 pileup events per BX
- μ , e and jets at exceedingly high rates
 - Increasing thresholds would affect physics performance
 - Performance of algorithms degrades with increasing pile-up

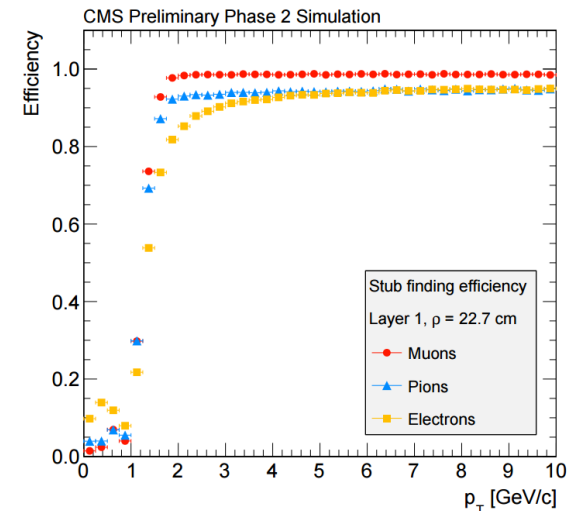


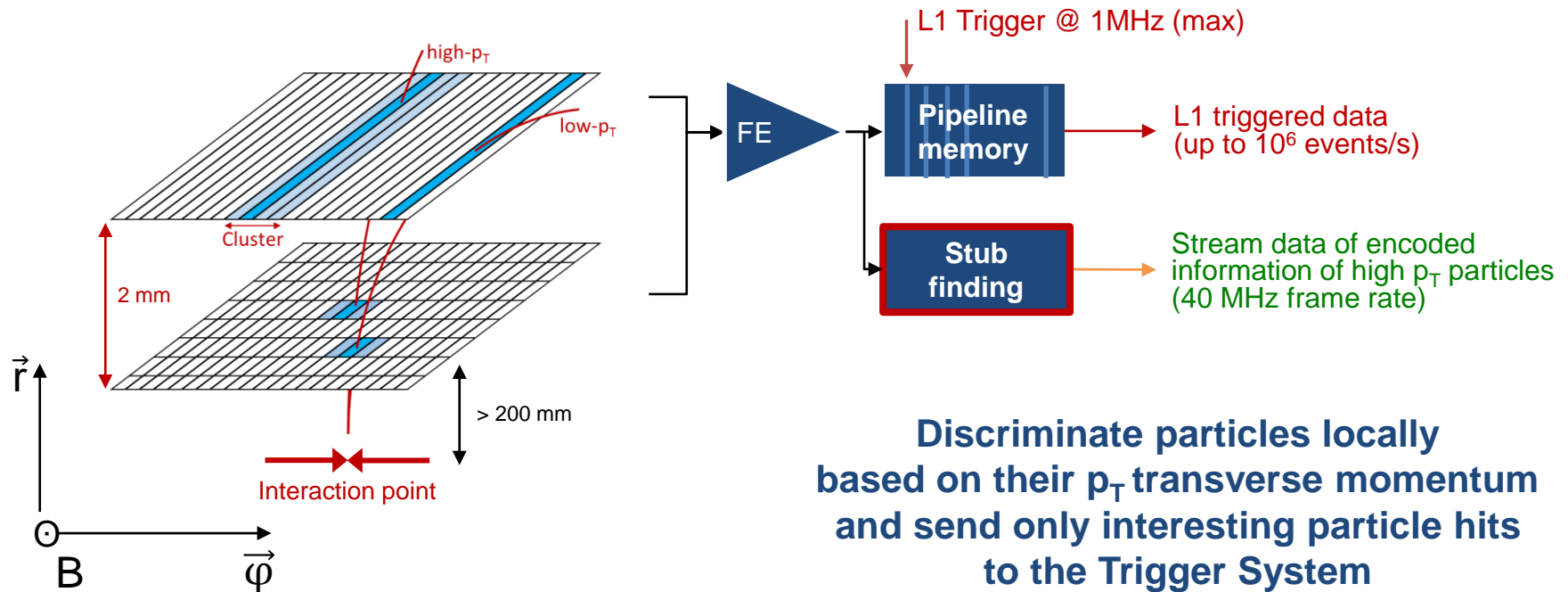
- **Track Triggering**

- Add tracking information to the Level-1 trigger decision to keep trigger rate at an acceptable level
 - Trigger Rate 100 kHz → 750kHz
 - Trigger Latency $3.2 \mu\text{s}$ → $12.5 \mu\text{s}$

- **Outer Tracker modules with p_T discrimination**

- Reject locally signals from low- p_T particles ($< 2\text{Gev}$)
- Reduce data volume by one order of magnitude making transmission feasible for the available power budget
- Simplify track finding algorithms





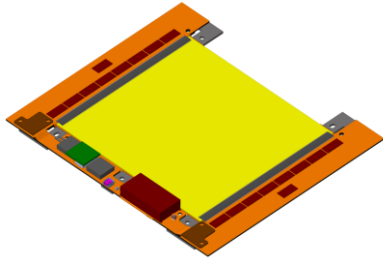
3.8T provided by the superconducting solenoid

- The CMS OT detector working principle of p_T discrimination
 - Exploit the strong magnetic field of CMS
 - Correlate signals between two closely spaced sensors to identify “stubs”
 - Stubs defined as a track coordinate + angle based on tracking window on parallel sensor
 - Transmit stub coordinates and momentum instead of a multiplicity of hits

Phase 2 CMS Outer Tracker

2S or Strip-Strip module

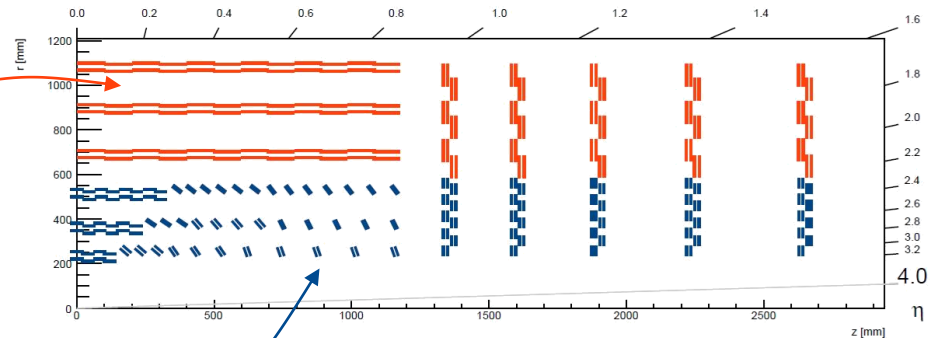
Outer Barrel



2 Strip sensors

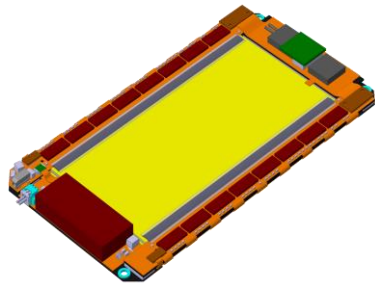
No strips: 2x 2 048 per side
 Strip size: 5 cm x 90 μ m
 Spacing: 1.8 mm and 4.0 mm
 Active area: 2 x 90 cm²
 Total 2S modules: ... 8 424

Phase 2 Outer Tracker Layout



PS or Pixel-Strip module

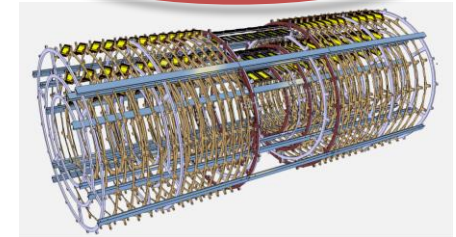
Inner Barrel



Pixel + Strip sensor

No strips: 2 x 960 = 1 920 strips
 Strip size: 2400 mm x 100 μ m
 No pixels: 32 x 960 = 30 720 pixels
 Pixel size: 1.5 mm x 100 μ m
 Spacing: 1.6 mm, 2.6 mm and 4.0 mm
 Active area: 2 x 45 cm²
 Total PS modules: ... 5 708

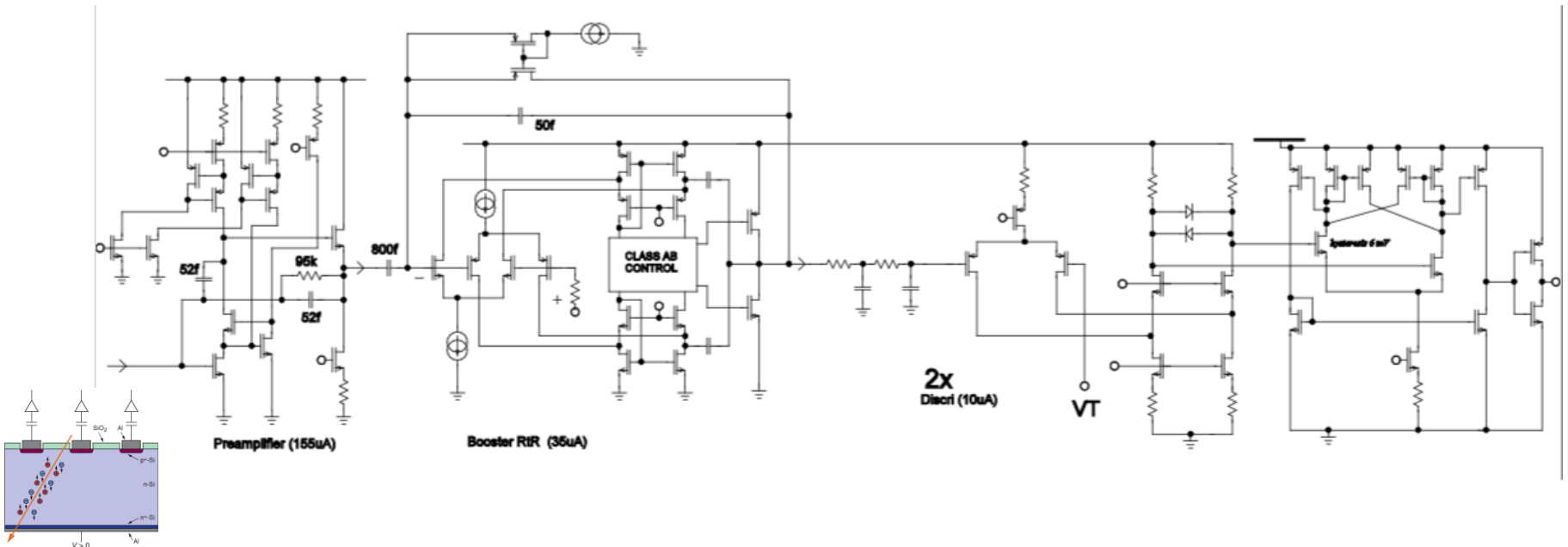
13 296 Modules
 44 Mstrips + 174 Mpixels
 200m² of silicon area



Power density: < 100 mW/cm²

[1] CMS collaboration. "The phase-2 upgrade of the CMS tracker." CMS-TDR-014 (2017).

[2] Abbaneo, Duccio. "Upgrade of the CMS Tracker with tracking trigger." Journal of Instrumentation 6.12 (2011): C12065.



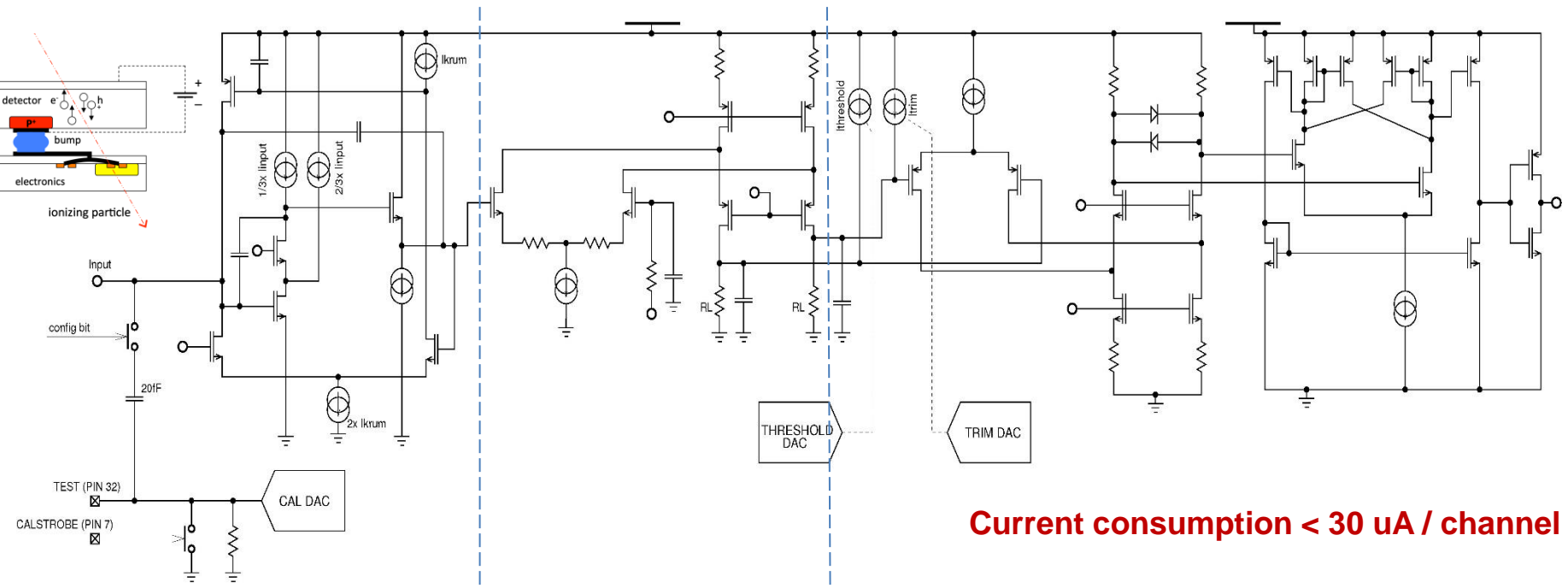
- Schematic design of the analog channel

- ❑ **Preamp:** regulated cascode transimpedance amplifier
- ❑ **Booster:** class AB buffer with active feedback for overshoot attenuation
- ❑ **3 stage discriminator**, folded cascode with resistive feedback (Discriminator for HIPs not shown)

Design parameters

Peaking time:	17 ns
Gain:	60 mV/fC
GBP:	2.7 GHz
ENC (5 pF input):	< 800 e ⁻
Max consumption:	250 μA

Designer: Jan Kaplon



Current consumption < 30 uA / channel

Preamplifier

Transimpedance Preamplifier with Krummenacher feedback leakage current compensation for n⁺ on p⁻ detectors

Shaper

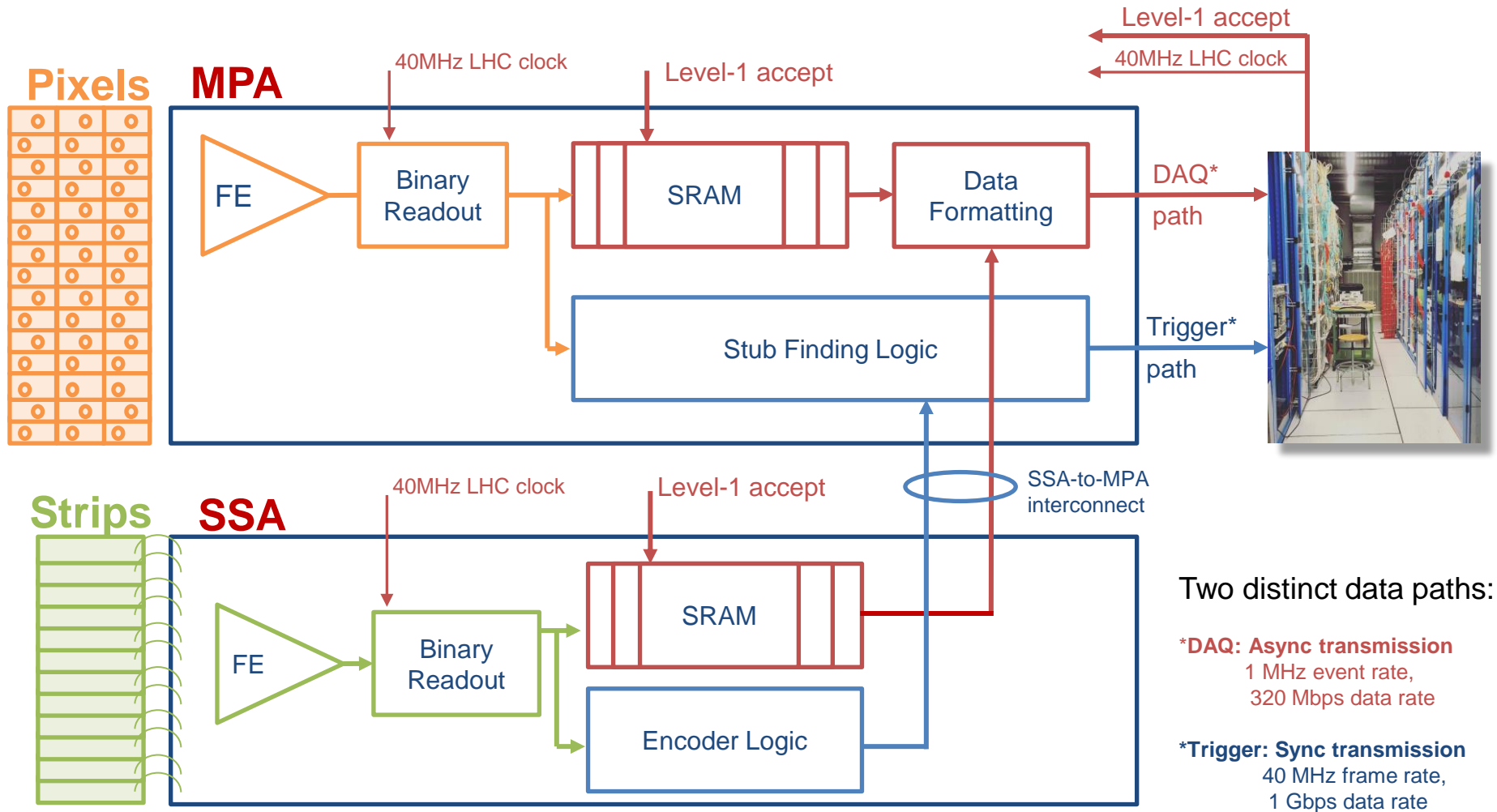
Single-ended to differential folded cascode stage with resistive load

Discriminator

- PMOS folded cascode input
- Swing limiter based on PMOS working in diode configuration
- Second stage with hysteresis (6mV)

Designer: Jan Kaplon

MPA-SSA Readout Concept



CMS Tracker Pixel-Strip (PS) module

■ Design Teams

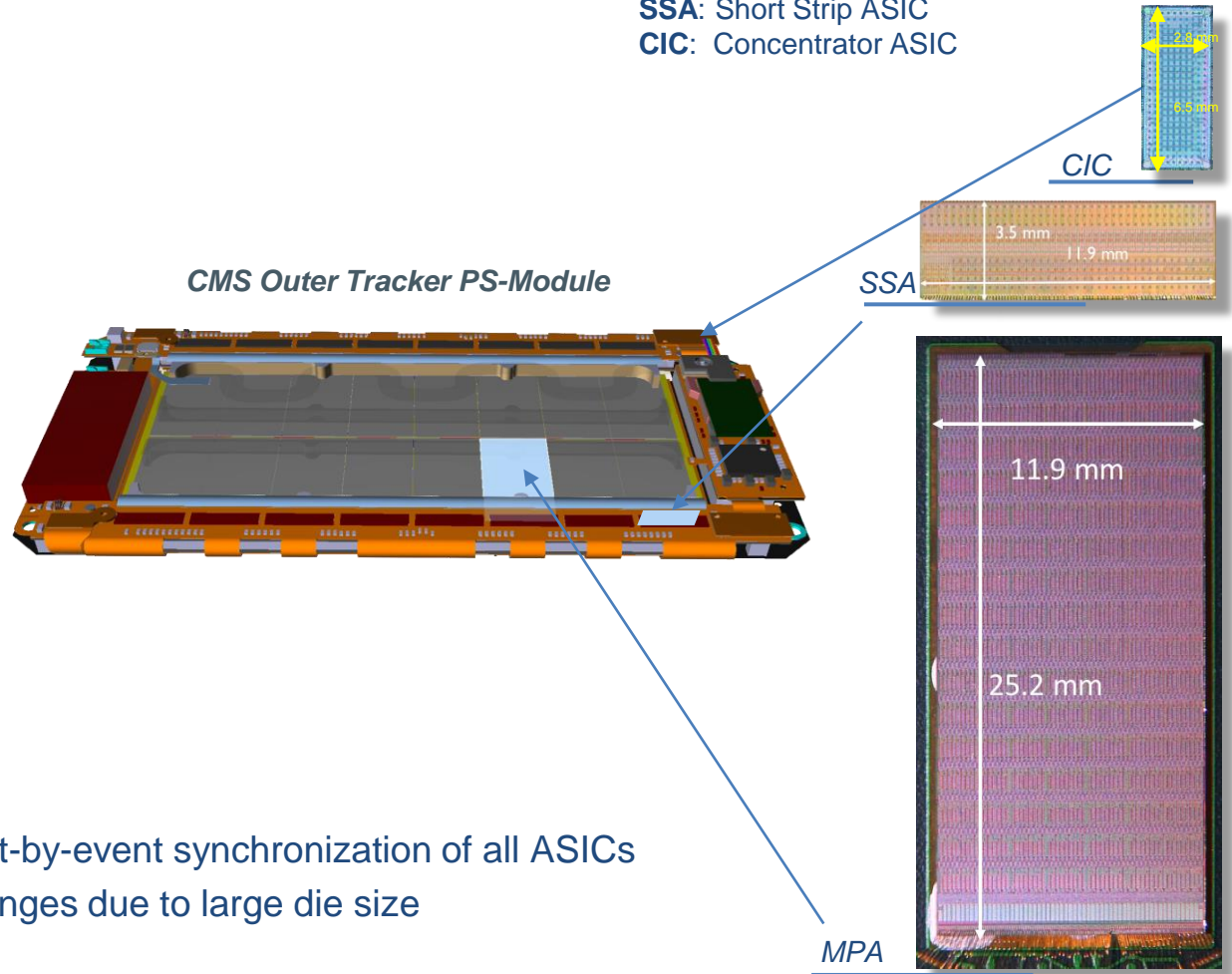
- **CERN (MPA, SSA, CIC)**
 - Alessandro Caratelli
 - Davide Ceresà
 - Jan Kaplon
 - Gianmario Bergamin
 - Kostas Kloukinas
 - Simone Scarfi

- **Lyon IPNL/IN2P3 (CIC)**
 - Luigi Caponetto
 - Geoffrey Galbit
 - Benedetta Nodari
 - Sebastian Viret

■ Challenging project

- Interoperability and event-by-event synchronization of all ASICs
- MPA ASIC design challenges due to large die size
- Low Power consumption

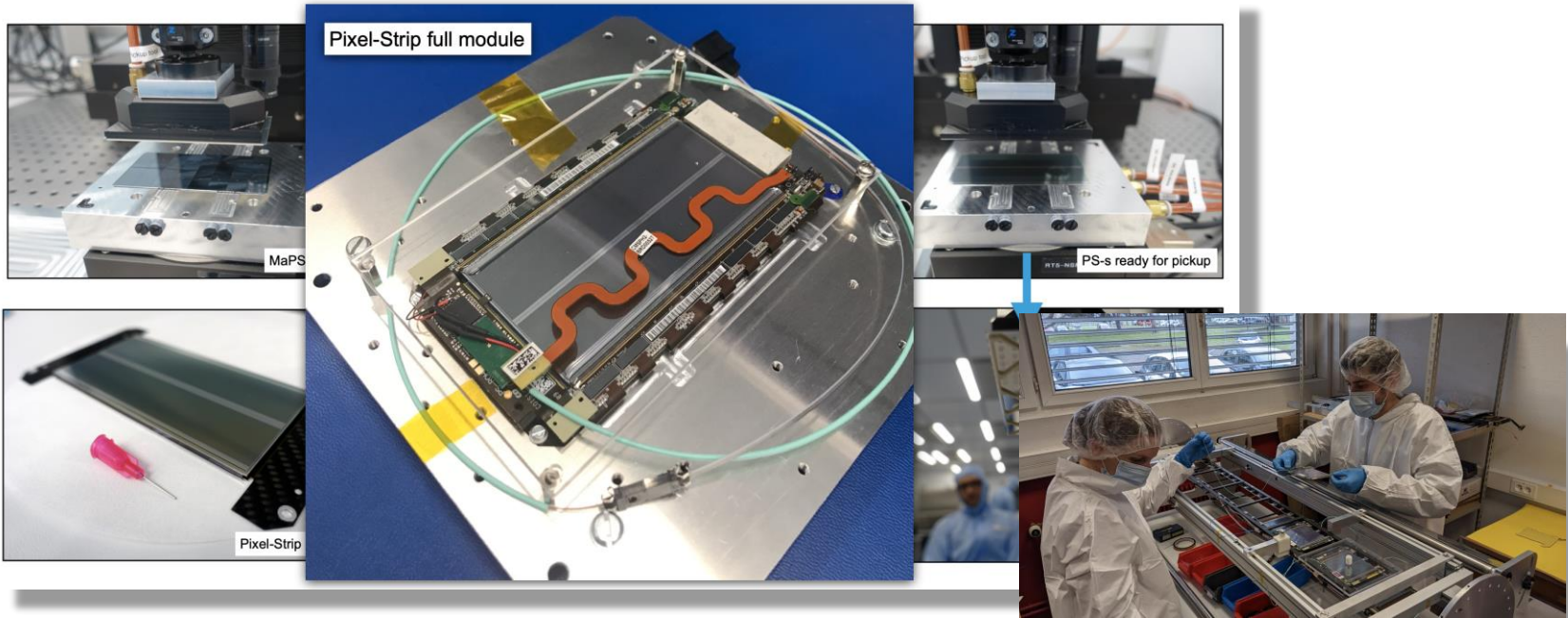
MPA: Macro Pixel ASIC
SSA: Short Strip ASIC
CIC: Concentrator ASIC



- Two full mask-set Engineering Runs on a 9-metal 65nm bulk CMOS process
- Prototype designs were tested
 - at die-on-board assemblies using custom made (FPGA based) test benches
 - at wafer level using a probe station at CERN
- Test routines include:
 - Scan-chain test for production defects
 - Functional test of digital circuits
 - Analog bias parameter characterization
 - Front-end characterization
 - Noise analysis
 - Serial ID and trimming in e-fuses

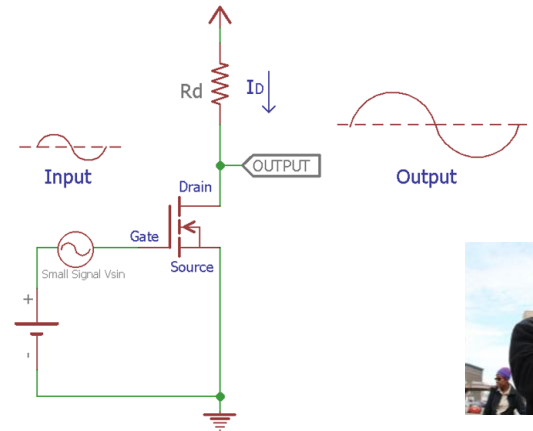
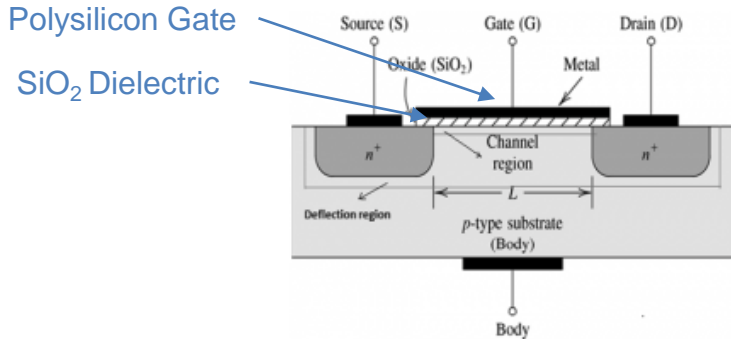


PS Module assembled

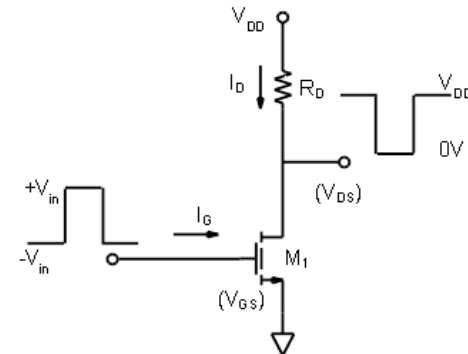
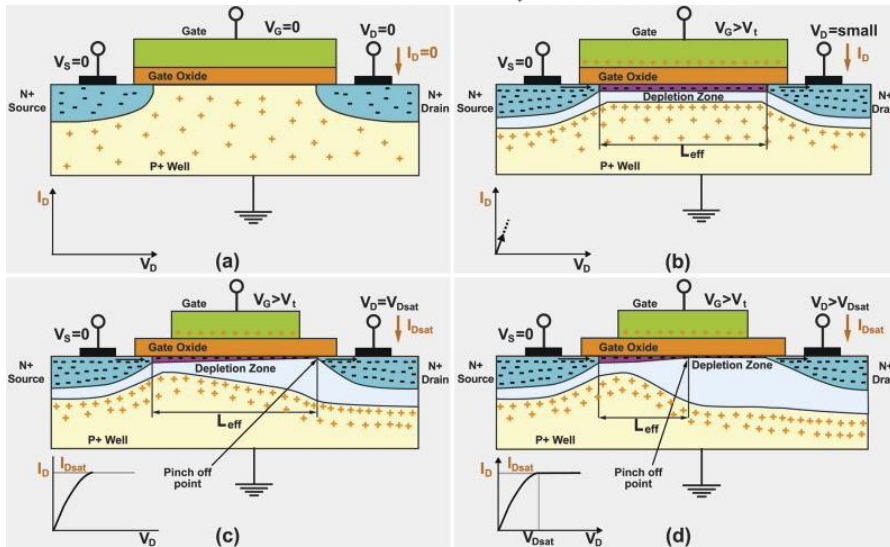


The basic element: the Transistor

MOSFET : Metal Oxide Field Effect Transistor



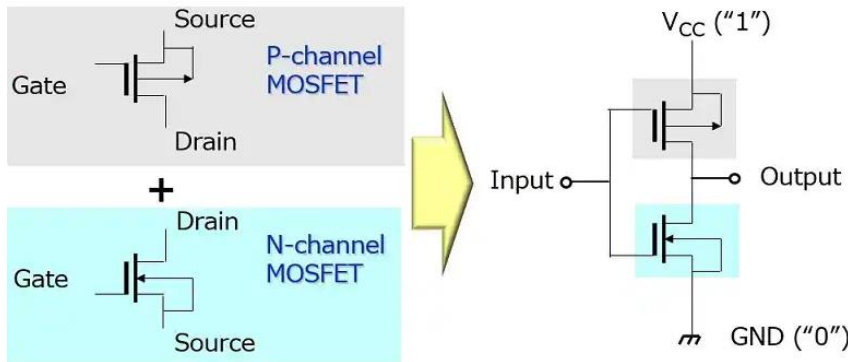
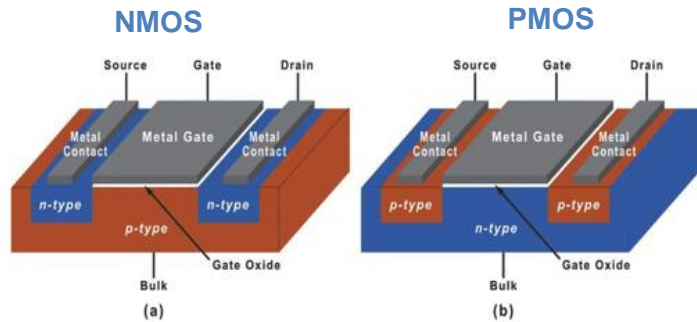
NMOS FET as an amplifier in Analog circuits



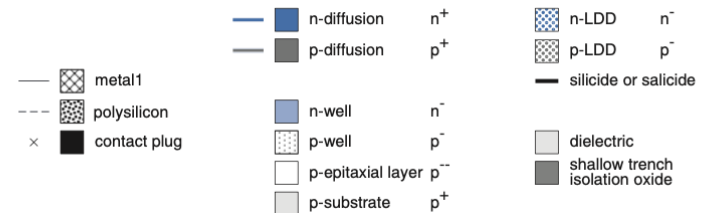
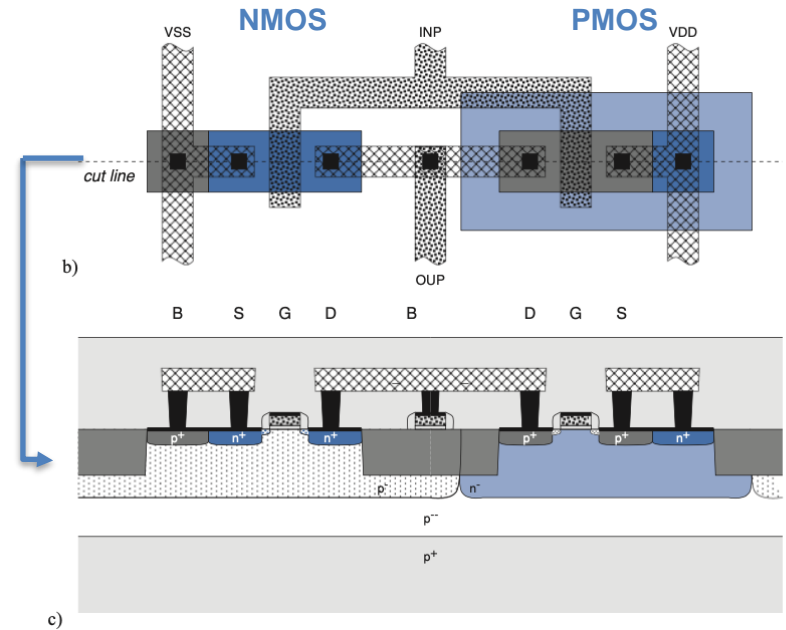
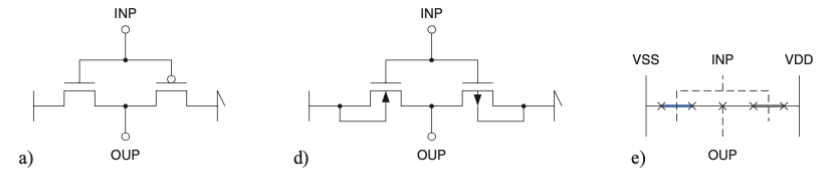
NMOS FET as a switch in Digital circuits

CMOS Transistors

CMOS : Complementary Metal Oxide Field Effect Transistor



Input	Output
0	1
1	0

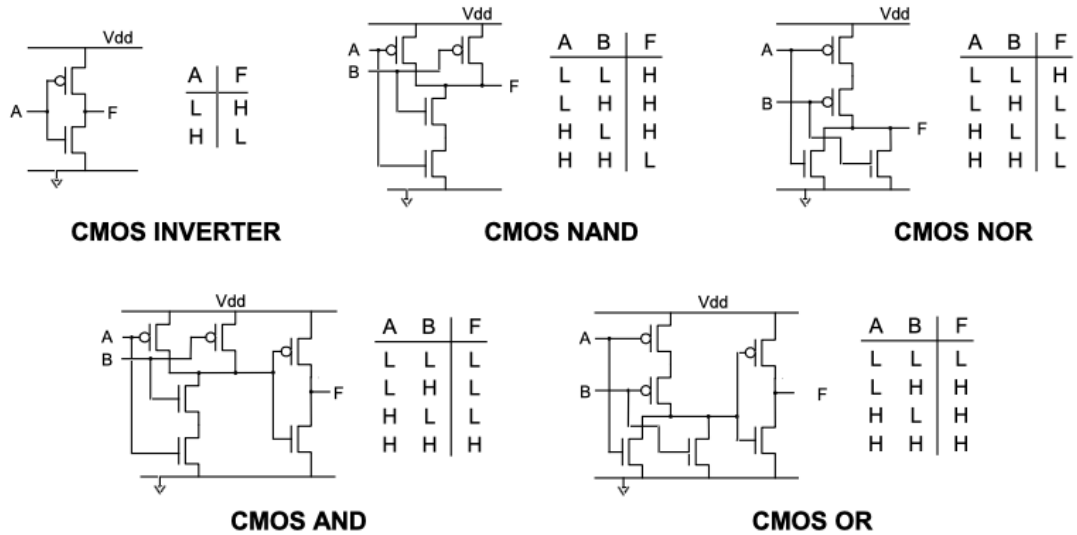


CMOS Inverter for Digital circuits

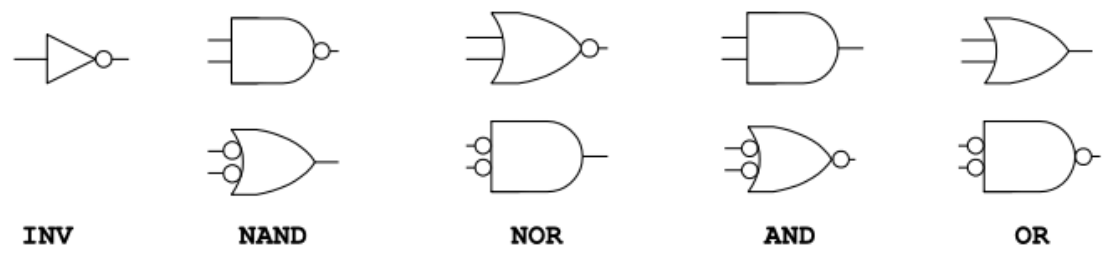
(solves the static current problem of NMOS circuits when the Output value is "0")

CMOS Logic Gates

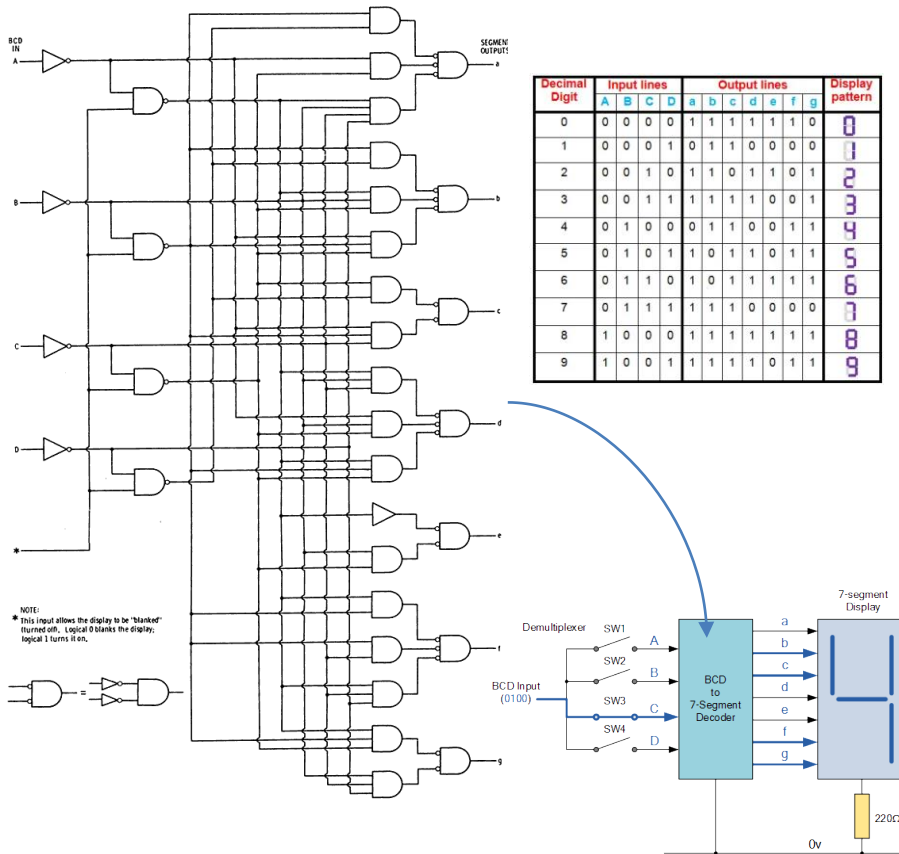
Basic CMOS Logic Gates and their truth table



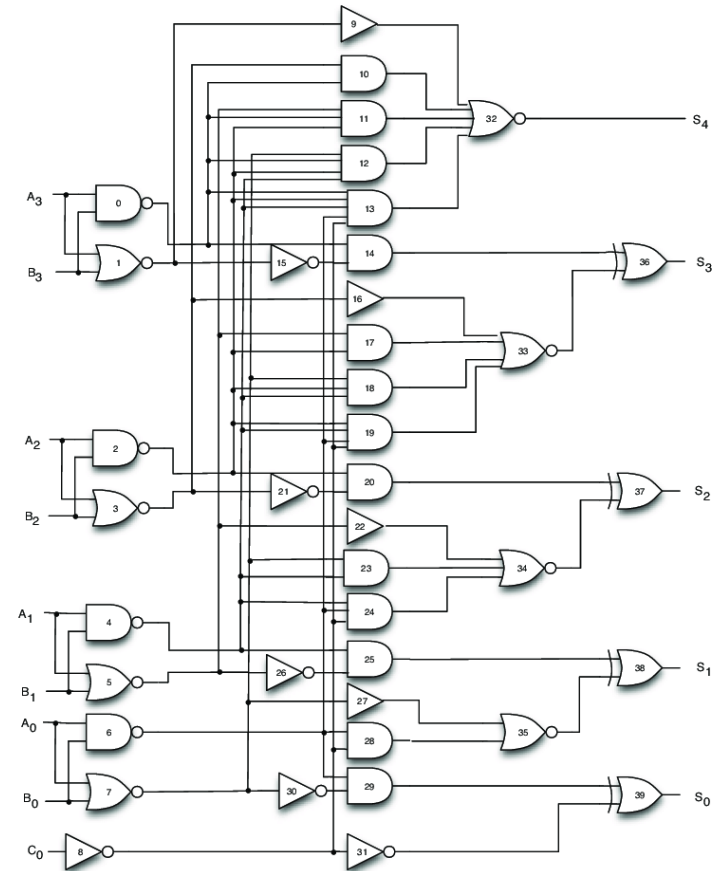
Basic CMOS Logic Gate Symbols



Logic Gate Circuit examples

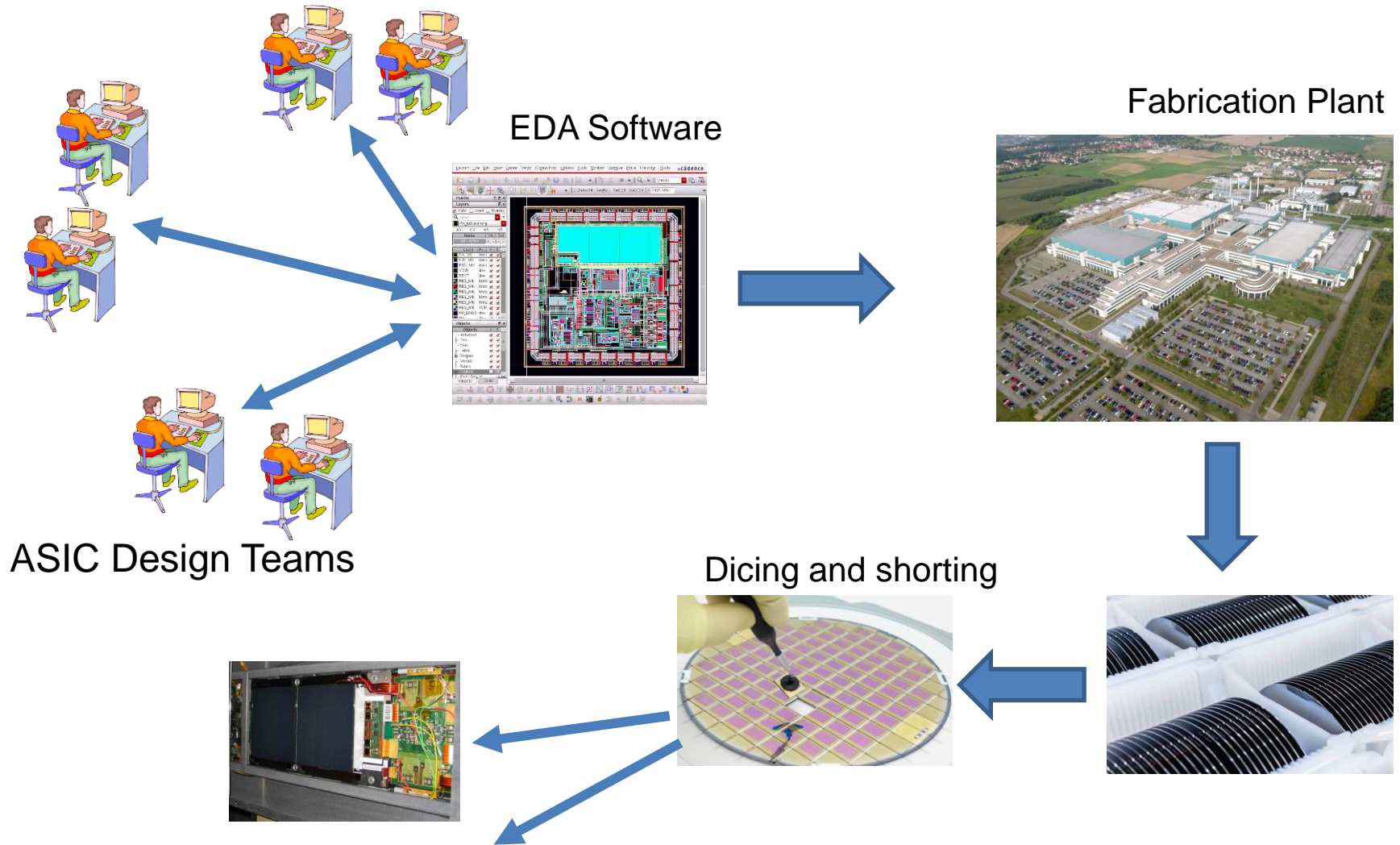


Binary to 7-segment display decoder

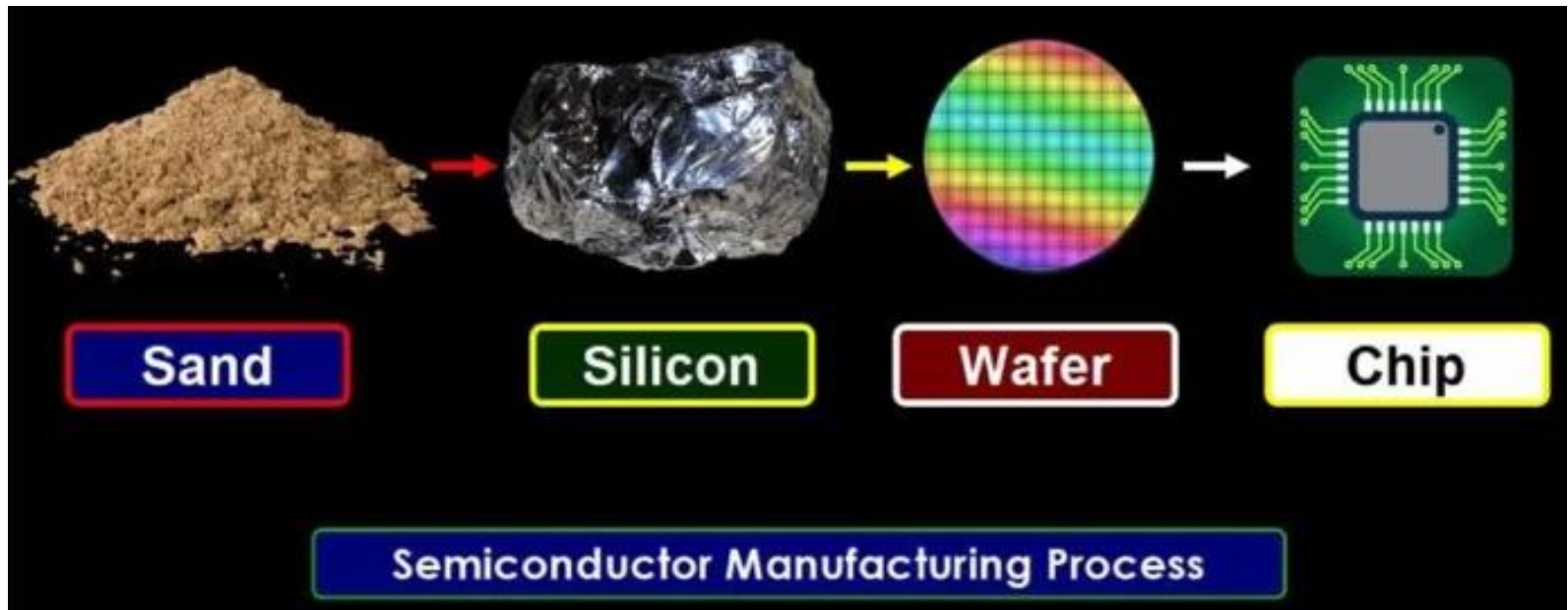


4-bit Adder with fast carry

ASIC design in HEP community



Semiconductor Manufacturing Process Flow Chart



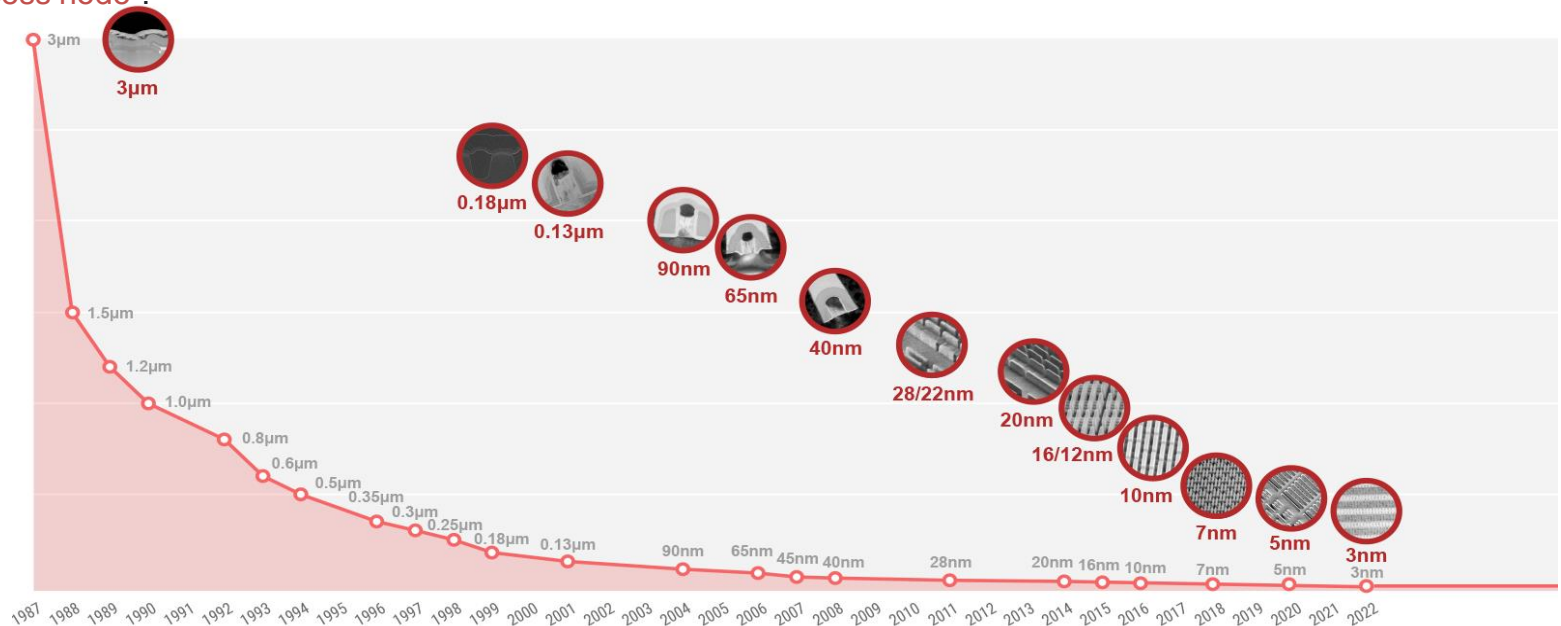
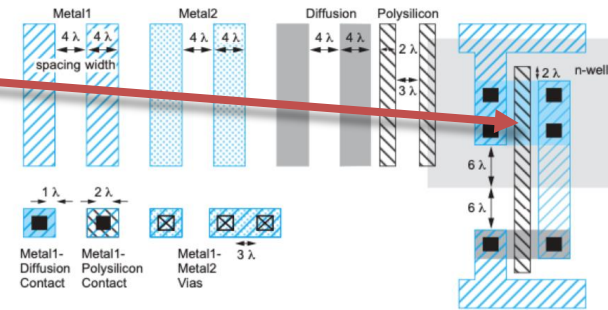
Feature Size and Process Node

Feature Size measured in Nanometers

The size of the features (the elements that make up the transistors) are measured in nanometers

Historically, the feature size referred to the **length of the silicon channel** between source and drain in field-effect transistors. Today, the feature size is typically the smallest element in the transistor.

A 25 nm process technology refers to features 25 nm or 0.025 μm in size. Also called a "technology node" and "process node".





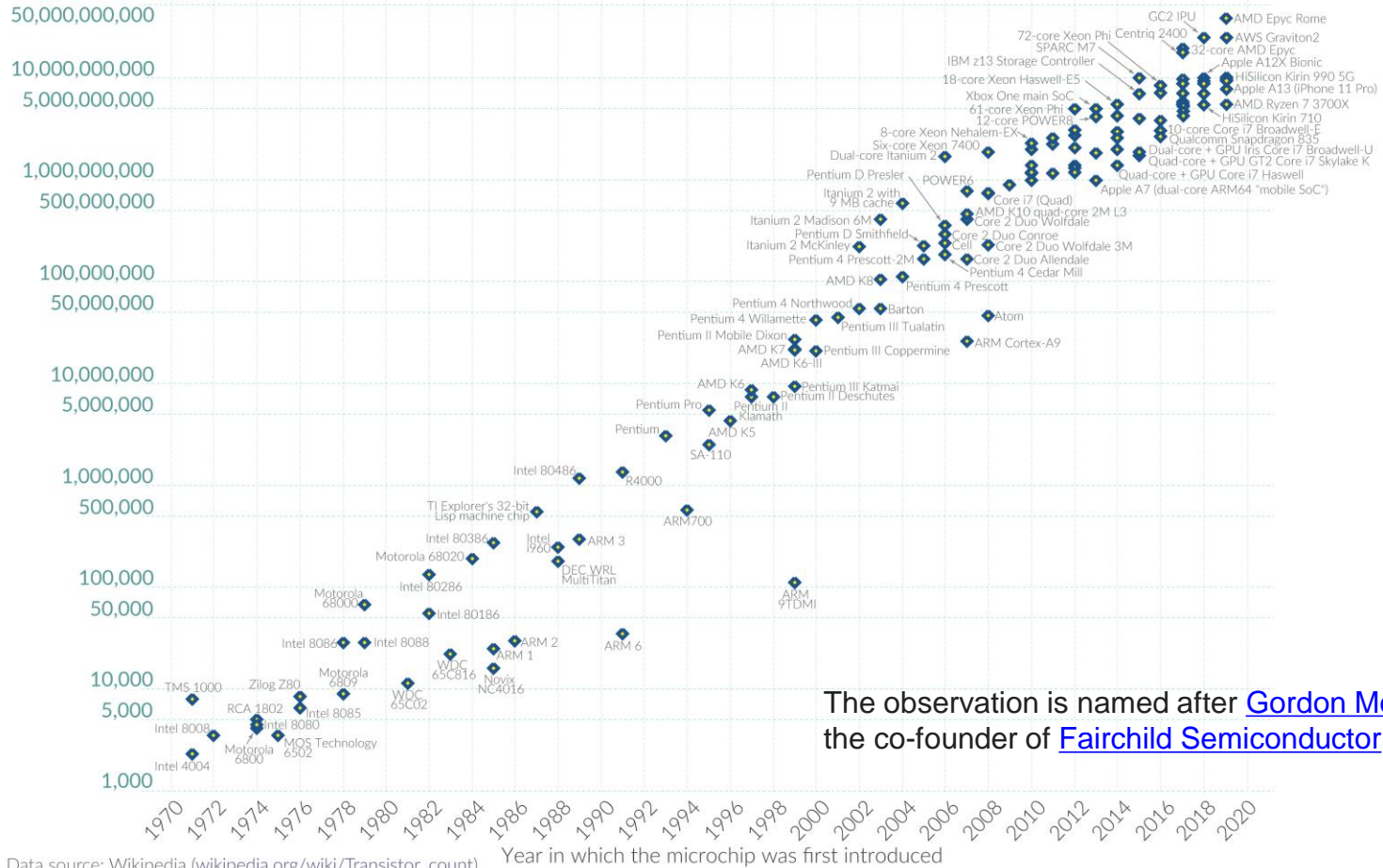
Moore's Law

Moore's Law: The number of transistors on microchips doubles every two years

Moore's law describes the empirical regularity that the number of transistors on integrated circuits doubles approximately every two years. This advancement is important for other aspects of technological progress in computing – such as processing speed or the price of computers.



Transistor count



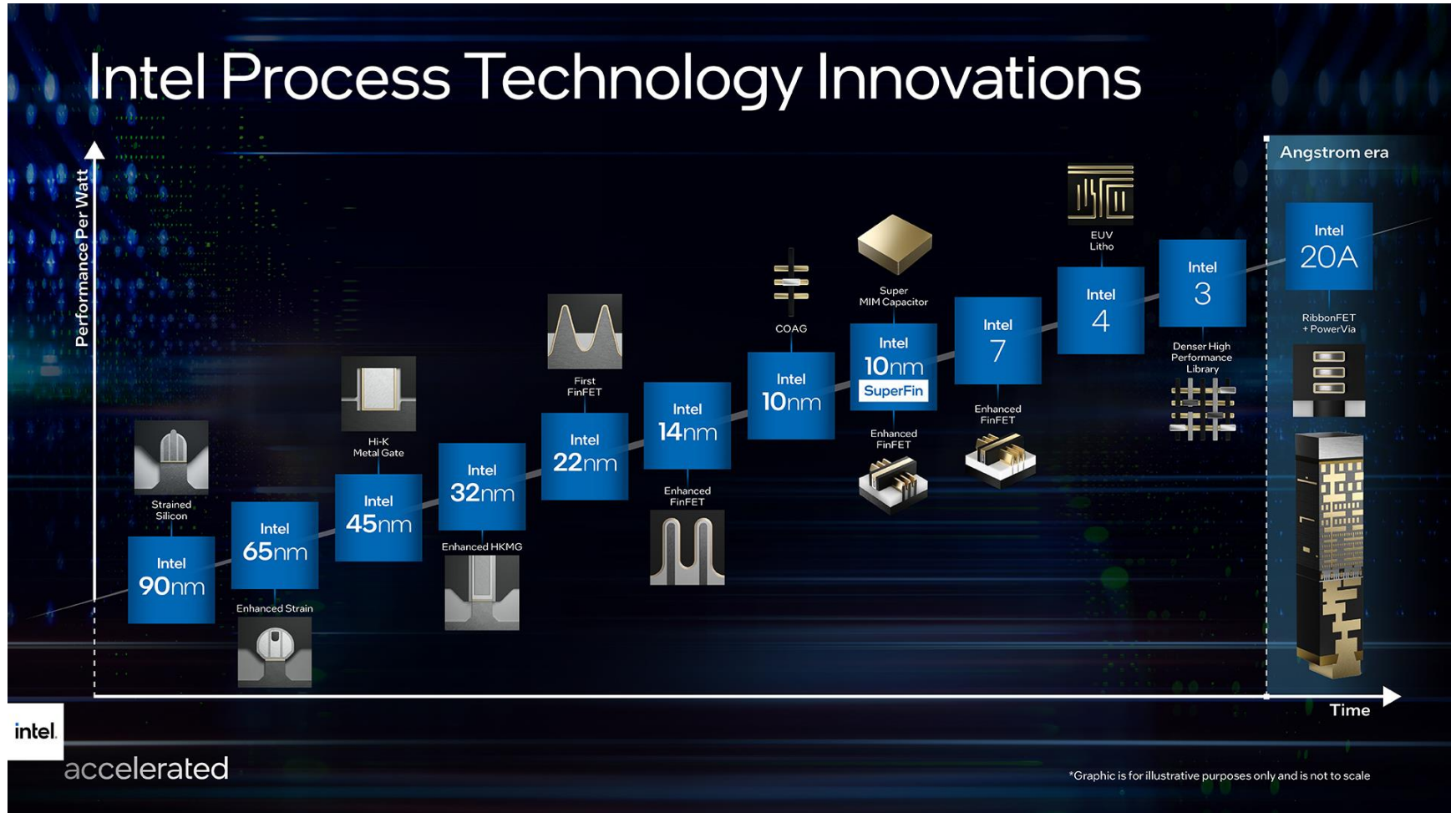
The observation is named after [Gordon Moore](#), the co-founder of [Fairchild Semiconductor](#) and [Intel](#)

Data source: Wikipedia (wikipedia.org/wiki/Transistor_count)

OurWorldinData.org – Research and data to make progress against the world's largest problems.

Licensed under CC-BY by the authors Hannah Ritchie and Max Roser.

Evolution of Intel Processors



CMOS Photomask Lithography

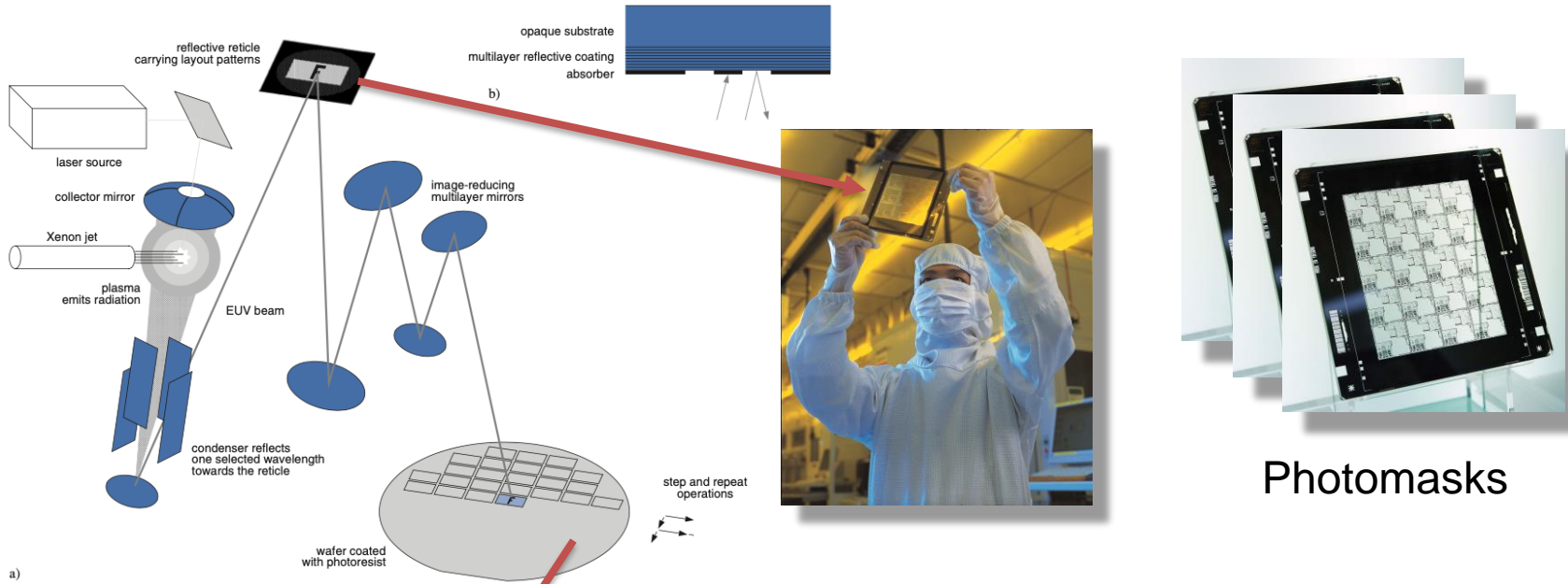
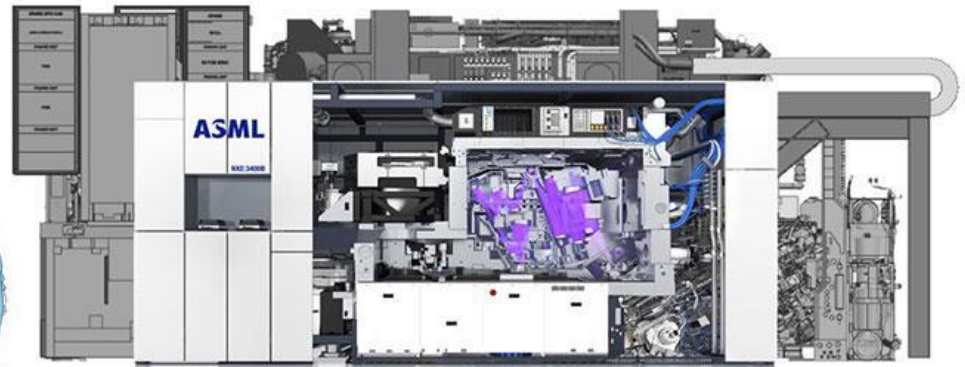
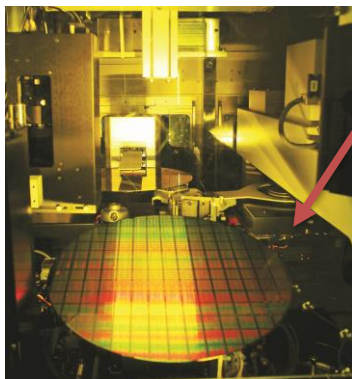
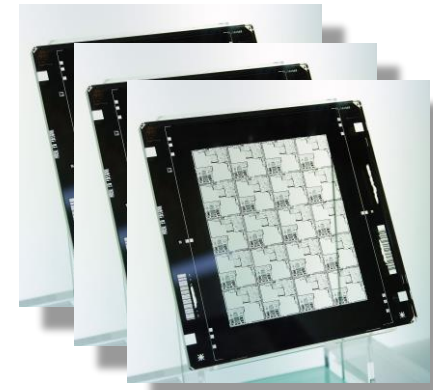


Fig. 14.25 Apparatus for EUV lithography (a) and cross section through a reflective mask (b), mirrors are same with no absorbing coating (greatly simplified).



US\$378 million EUV lithography machine

CMOS Fabrication

1) Wafer preparation

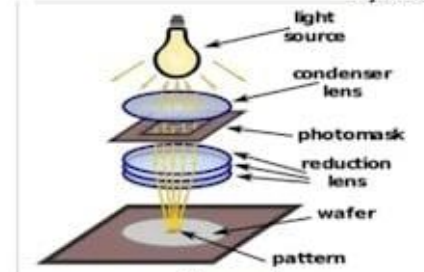


wafer ingot

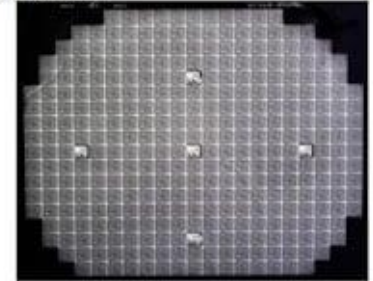


wafer sliced, polished and cleaned

2) Pattern transfer

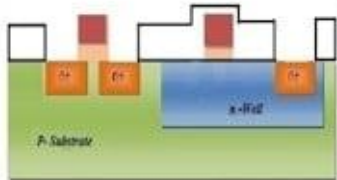


lithography

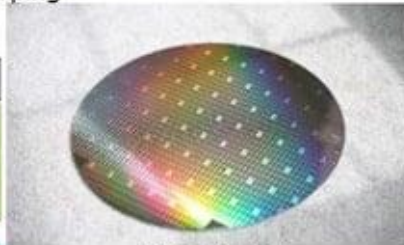


mask

3) Doping

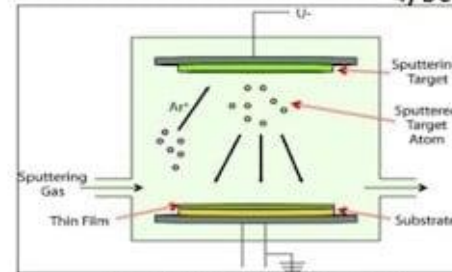


doped diagram



doped wafer

4) Deposition

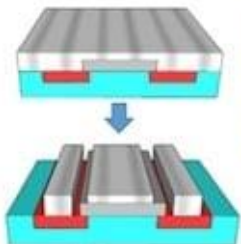


physical vapor deposition



metal deposition

5) Etching



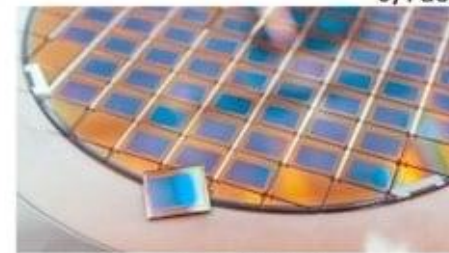
etching process



etched metal



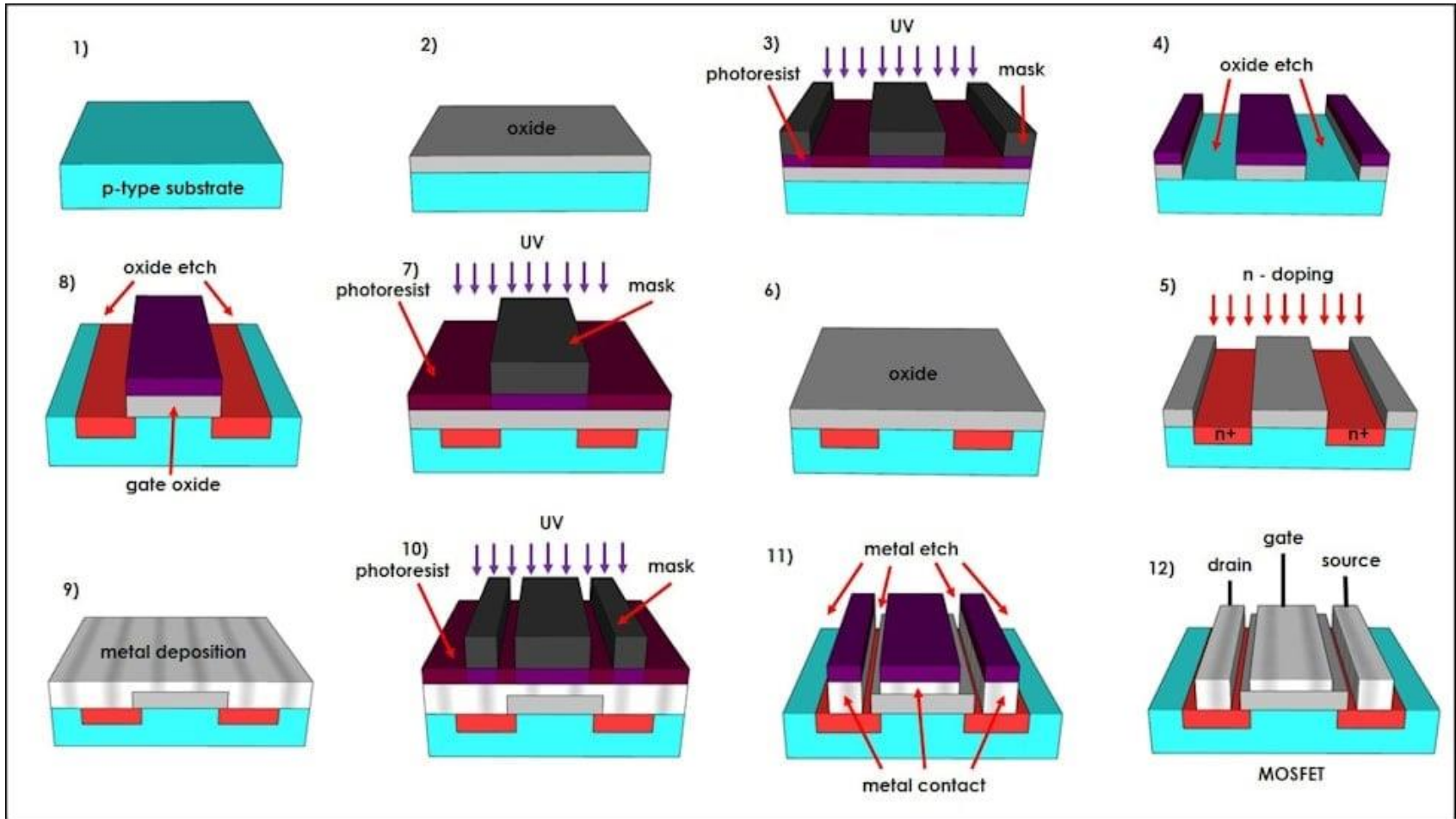
6) Packaging



diced wafer



microchip





Semiconductor Foundry (Plant)



Construction cost
of a modern Plant: \$5 - \$20 billion



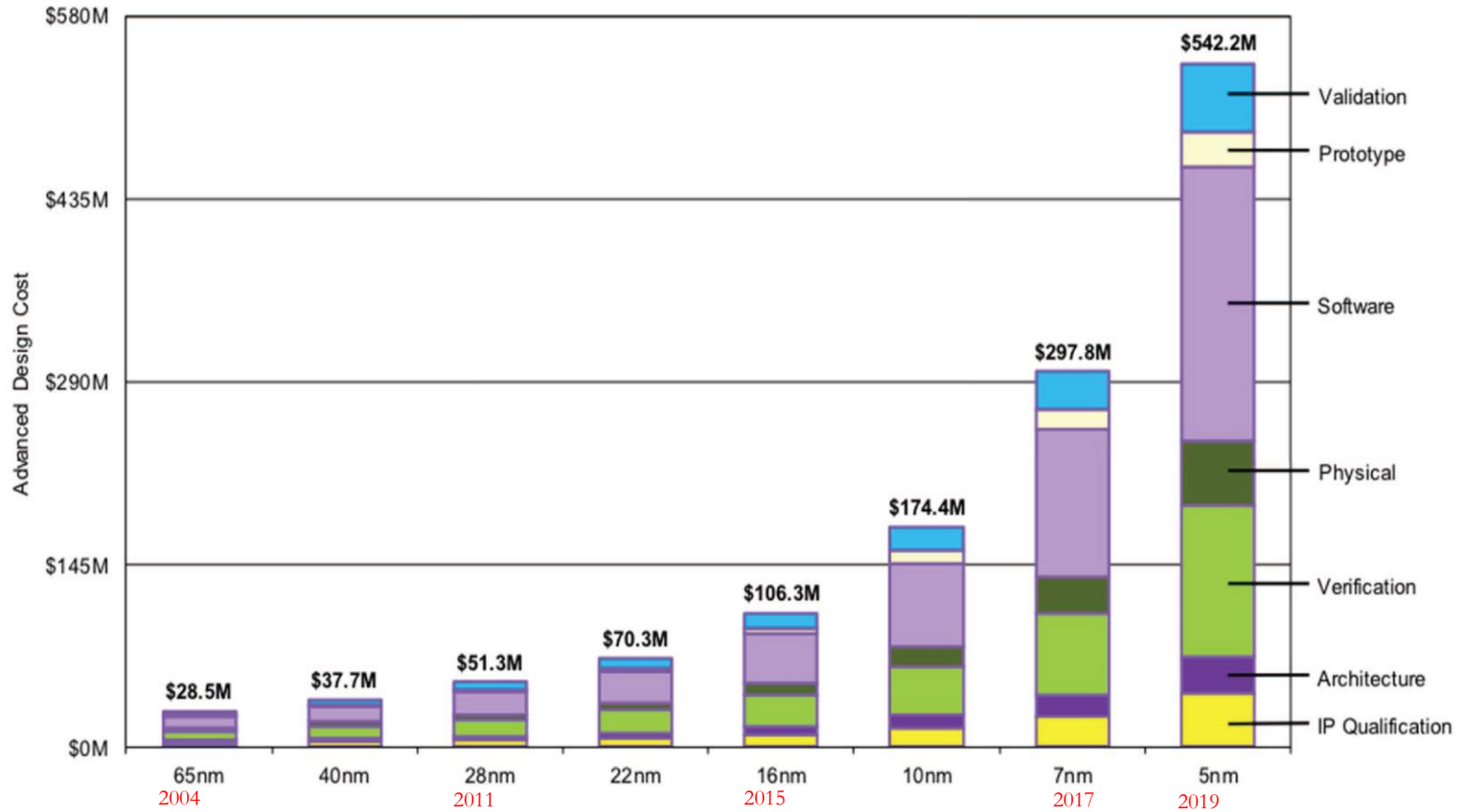
A Major Fab

Location	
AP1 Hsinchu, Taiwan	
AP2B AP2C (<i>Under construction</i>) Tainan, Taiwan	 
AP3 Longtan, Taiwan	
AP5 Taichung, Taiwan	
AP6 (<i>Under construction</i>) Chunan, Taiwan	



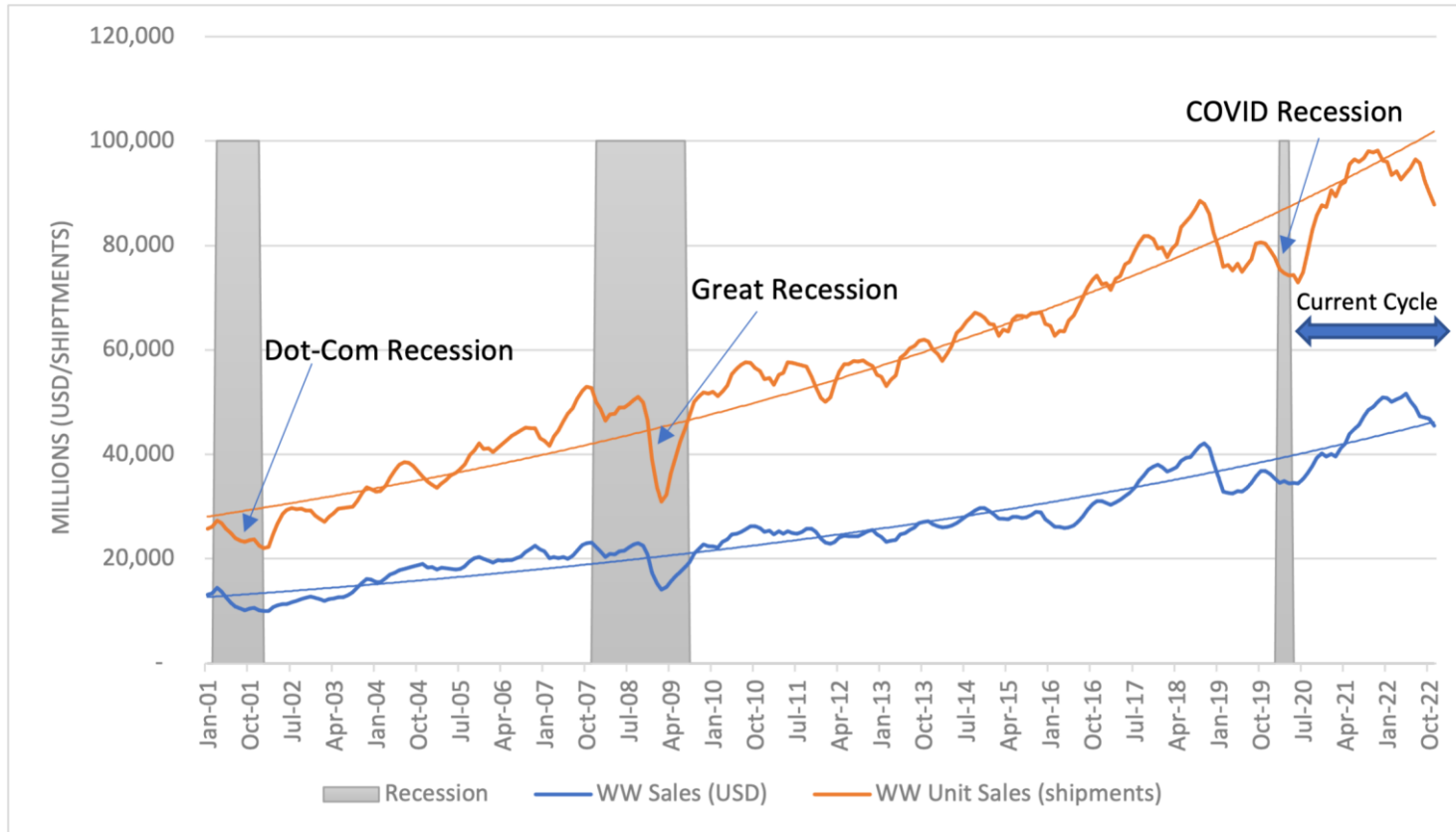


ASIC development costs



Chip Design and Manufacturing Cost under Different Process Nodes: Data Source from IBS*

* According to the survey from the *International Business Strategy Corporation (IBS)*, the increase of design cost for each generation technology has exceeded 50% after 22 nm process, including EDA, design verification, IP core, tape-out, and so forth.



Source: WSTS and SIA analysis

[1] McKinsey & Company. [The semiconductor decade: A trillion-dollar industry](#). April 1, 2022.



Summary

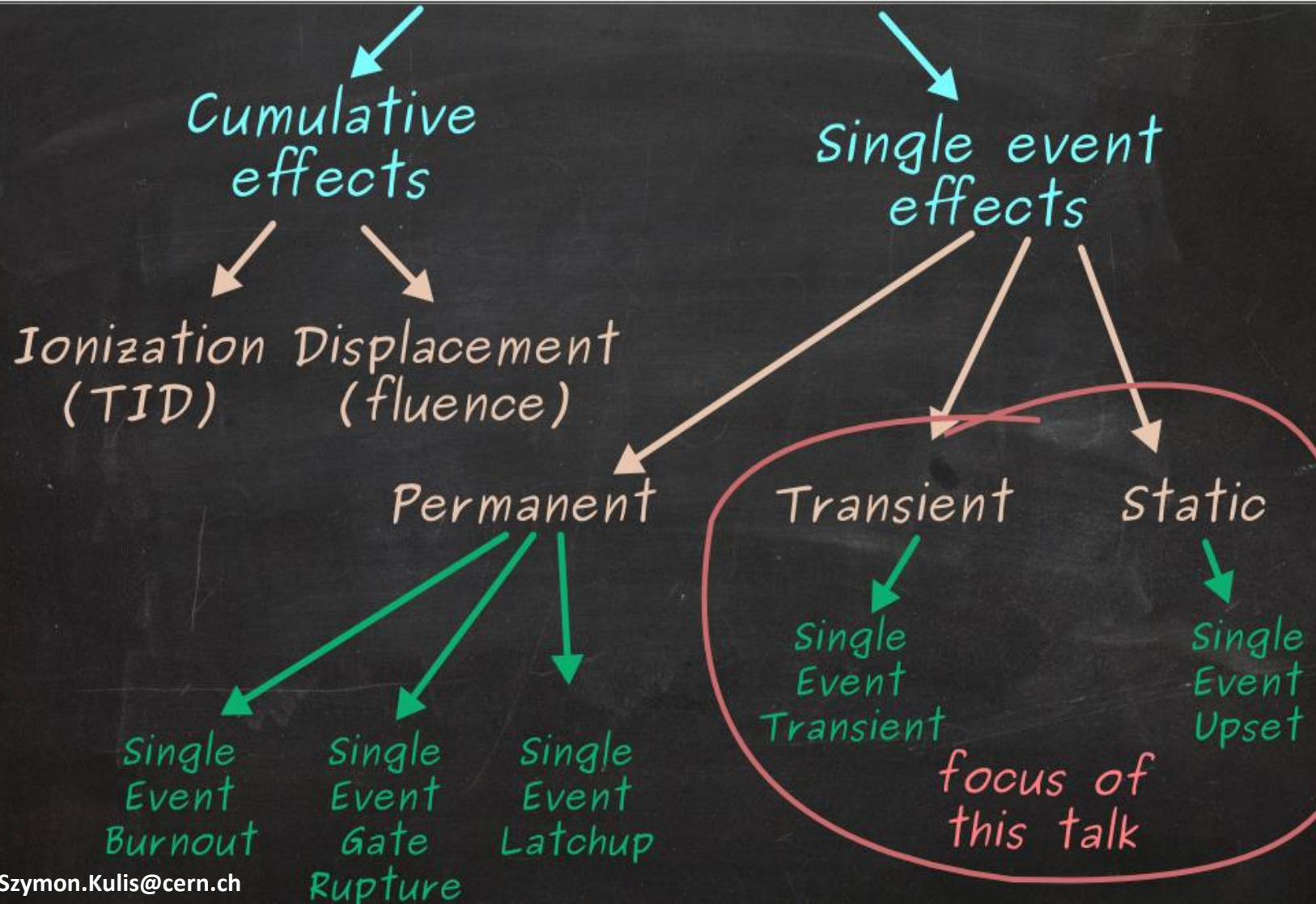
- Application-specific integrated circuits (ASICs) are the enabling technology for many complex detector systems
 - Customised electronic circuits for a well-defined application
 - Typically manufactured in CMOS processes

- Pros of ASICs
 - **Optimised** for demanding requirements: size, power, functions, performance,...
 - **Miniaturised**, ideal for high density HEP (large number of channels)
 - High **quality with low unit cost** on large scale
 - **Radiation hardness** using commercial processes

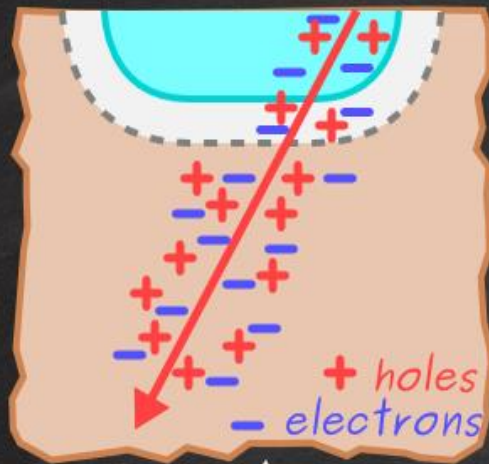
- Cons of ASICs
 - **Big development investment** required in both time and cost increasing as functionality (= complexity) increases
 - **Unchangeable** once complete, unless a lot of flexibility is built-in(adds complexity)
 - **Substantial design and evaluation** requiring specialist skills (industry pays well!)

A nighttime photograph of the Globe of Science and Innovation at CERN, illuminated from within, set against a dark blue sky with stars and a shooting star.

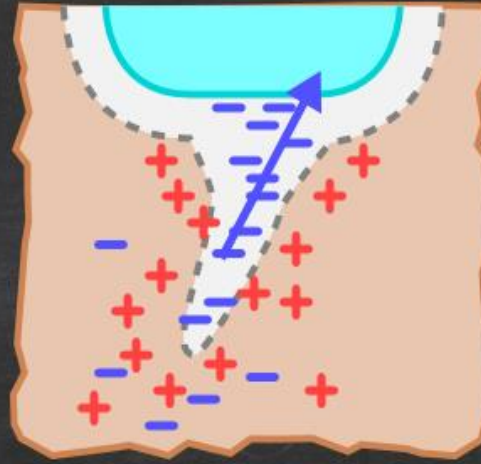
Thank You



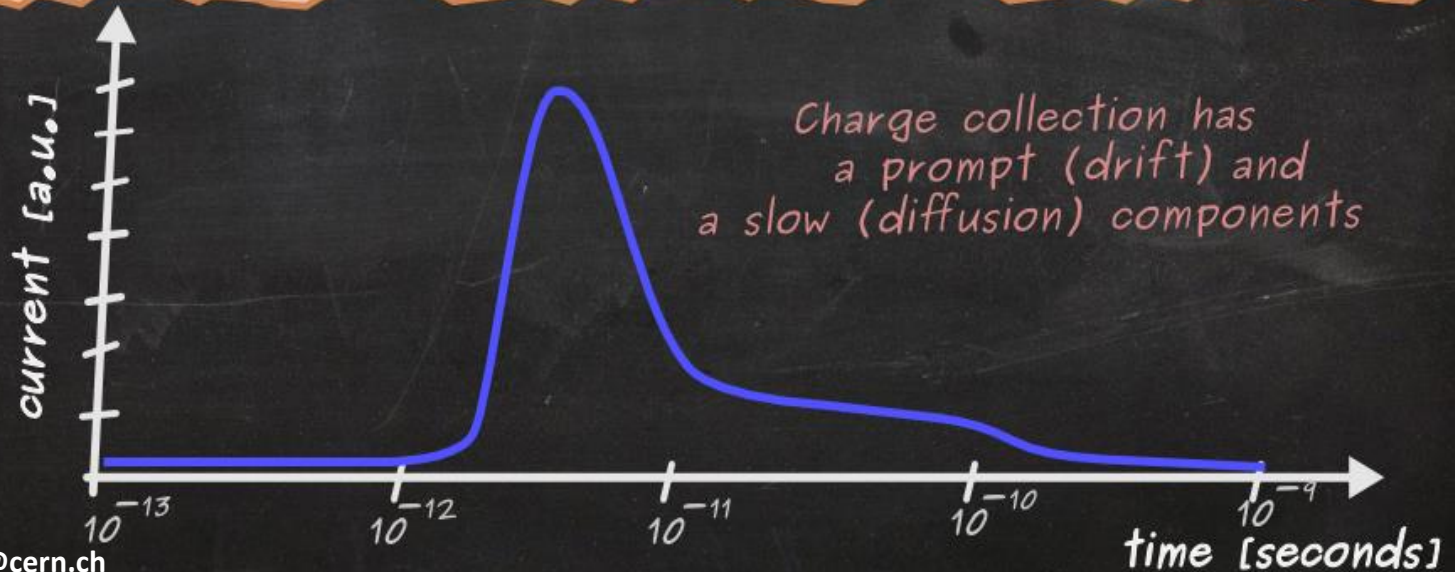
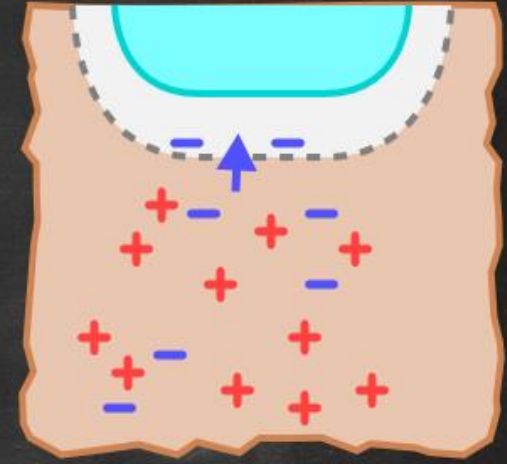
ionization ($t=0$)

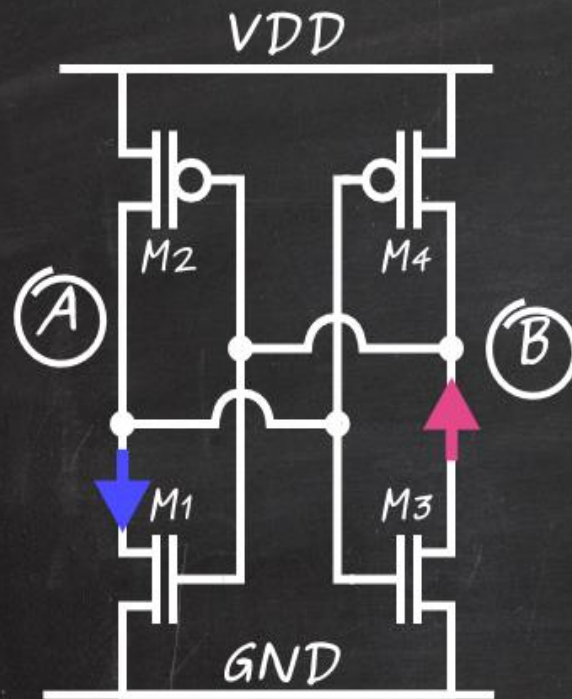


drift ($t=10ps$)



diffusion ($t=100ps$)



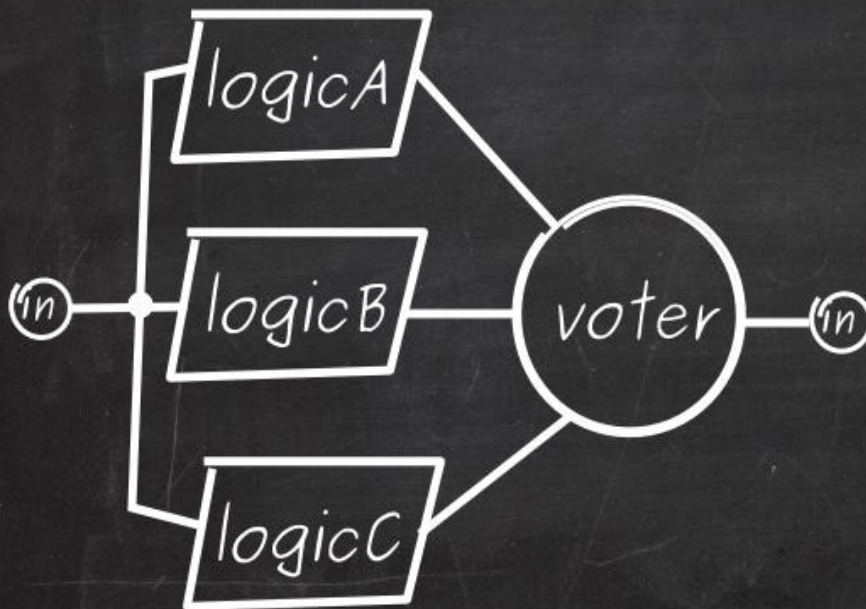


SRAM cell
(pass gates missing)

- 1) initial state : $A = VDD, B = GND$
- 2) charge deposited at drain of M1
- 3) transient current changes temporary the state of node A ($VDD \rightarrow GND$)
- 4) before the desposited charge is evacuated, the second inverter (M3-M4) switches (node B $GND \rightarrow VDD$)
- 5) The change of node B enforces the wrong state at node A \rightarrow the error is latched into the memory cell

How much charge is needed to flip the value?

Normally, the three blocks give the same output



A	B	C	Z
0	0	0	0
0	0	1	0
0	1	0	0
1	0	0	0
0	1	1	1
1	0	1	1
1	1	0	1
1	1	1	1

voter truth table